

# Noise Parameters of FET's: Measurement, Modeling and Use in Amplifier Design



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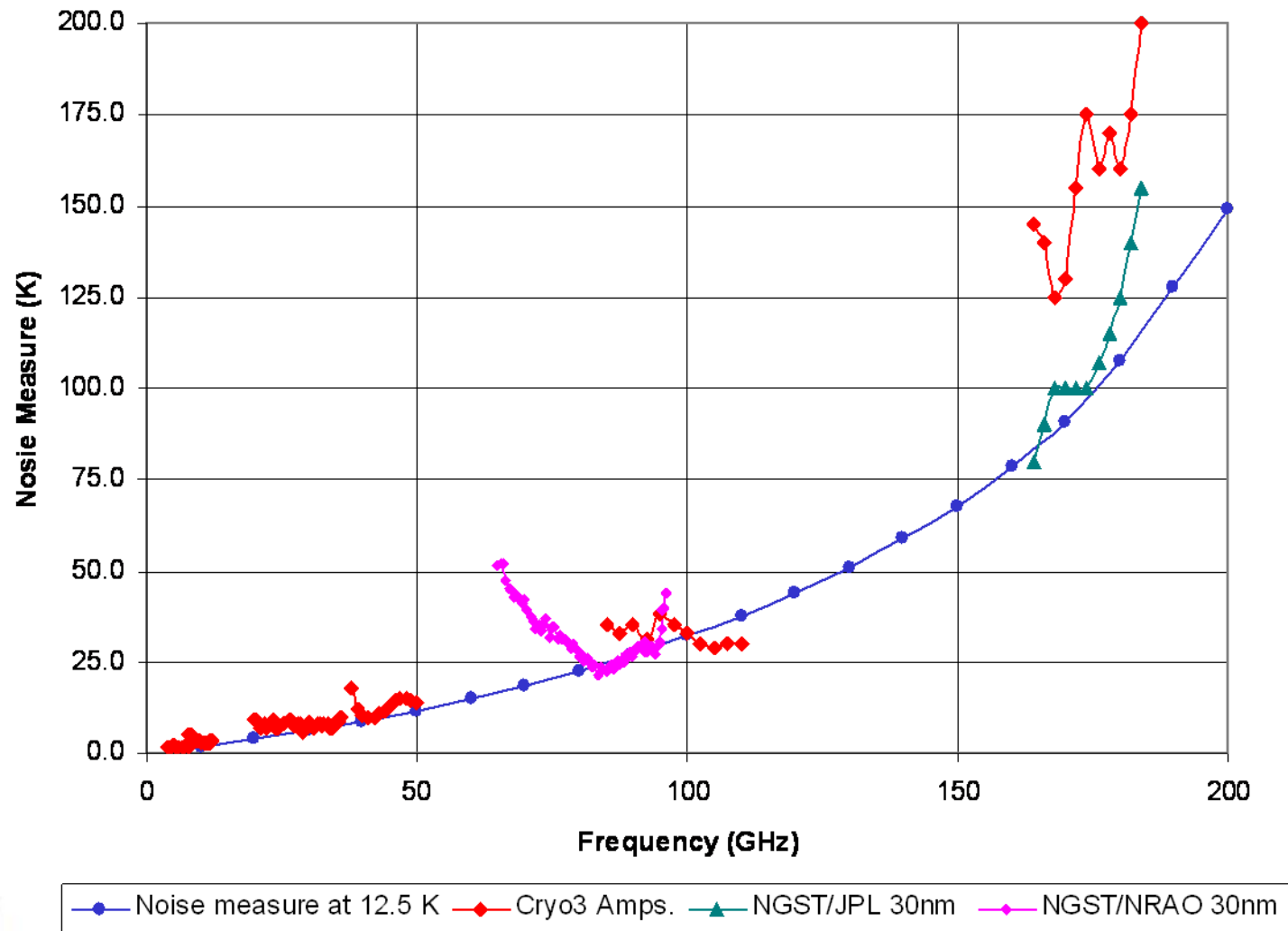
Atacama Large Millimeter/submillimeter Array  
Expanded Very Large Array  
Robert C. Byrd Green Bank Telescope  
Very Long Baseline Array



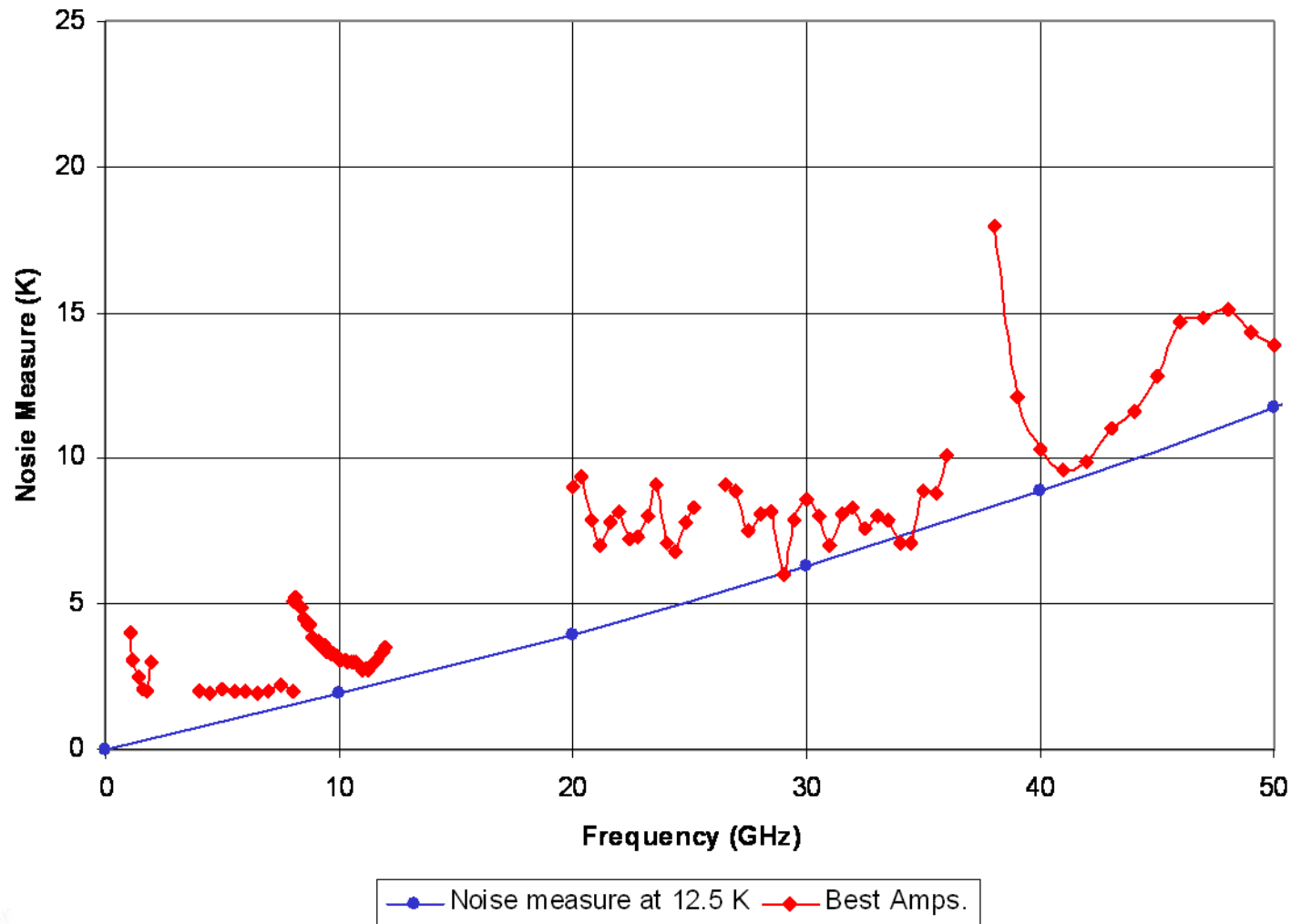
# Outline

- State-of-the-art
- Noise temperature measurement methods employed at CDL
- Review of the sources of error
- Some properties of signal and noise models of FETs
- Method of measurement of noise parameters at cryogenic temperatures
- Optimal noise bias of a FET – lessons for future improvements
- Effects observed but not understood
- Final observations

# $M_{\min}$ Prediction (1991) and State of the Art (2009)



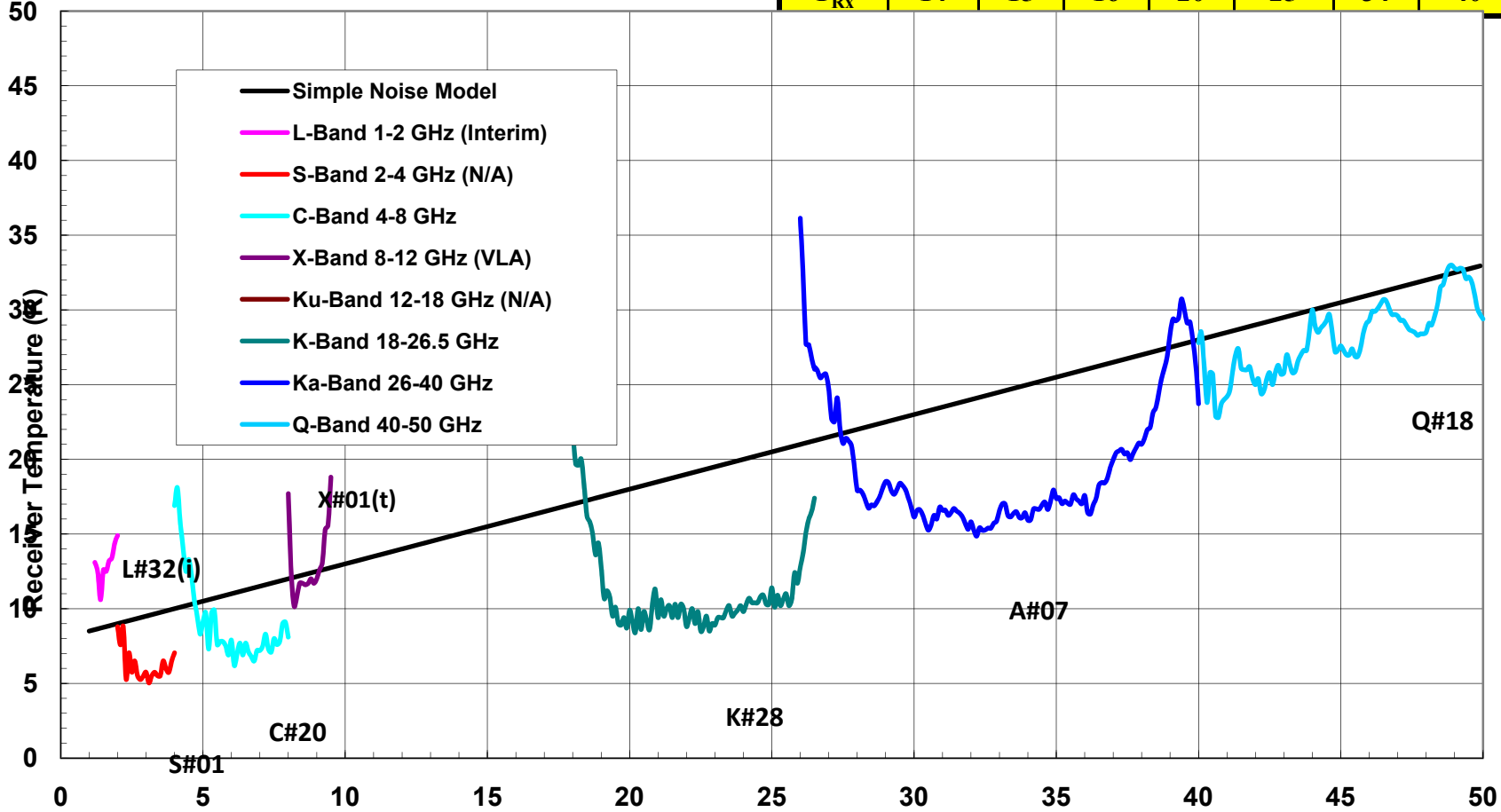
# $M_{\min}$ Prediction (1991) and State of the Art (2009)



# VLA/EVLA

## $T_{RX}$ versus Frequency

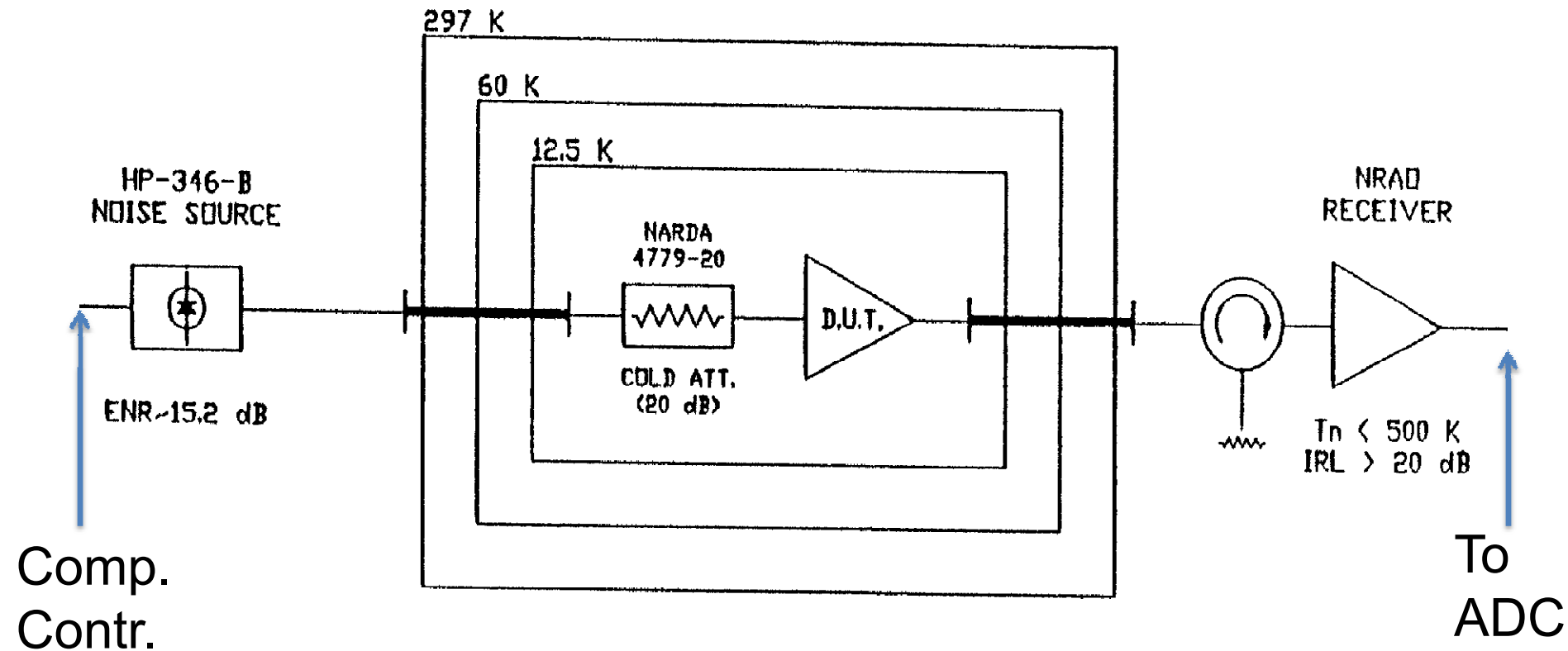
EVLA Project Book - $T_{RX}$ Requirements (Band Center)								
Band	L	S	C	X	Ku	K	Ka	Q
$T_{RX}$	14	15	16	20	25	34	40	48



R. Hayward  
NRAO, Socorro, NM

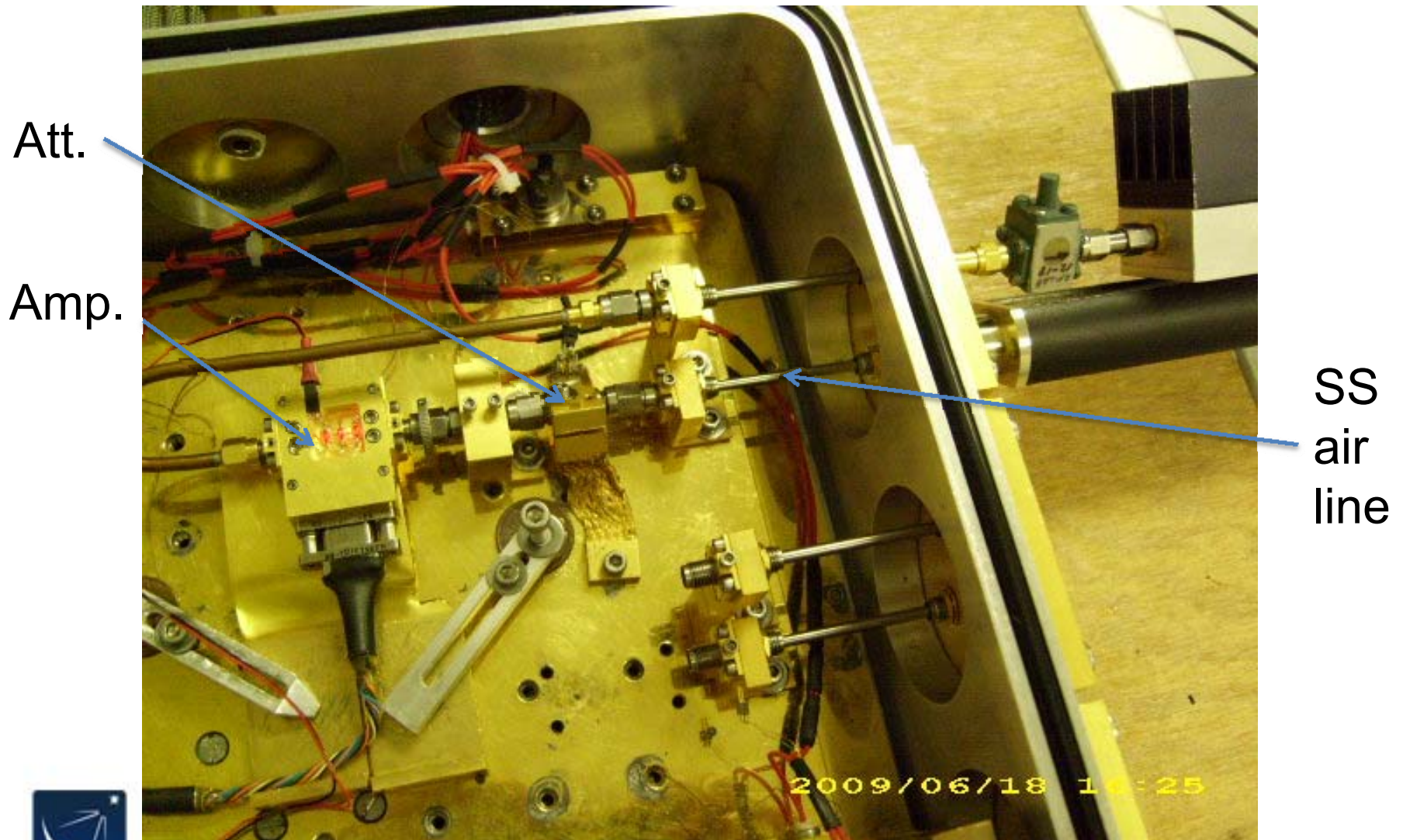
$T_{RX} = m \cdot F + b ; m = 0.5^{\circ}K / GHz ; b = 8^{\circ}K$

# Cold Attenuator Measurement Method

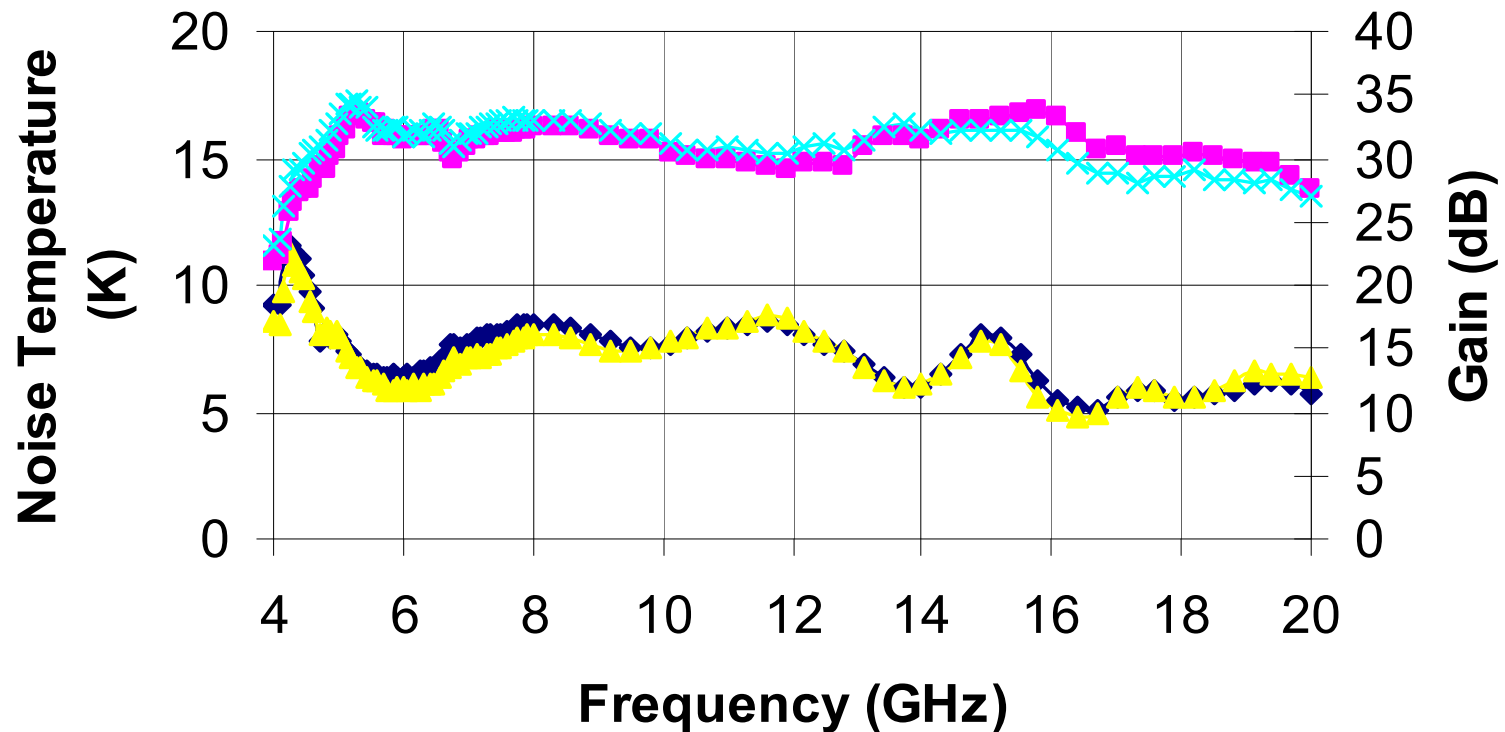


Main source of error: Uncertainty in calibration of ENR

# Cold Attenuator Noise Measurements

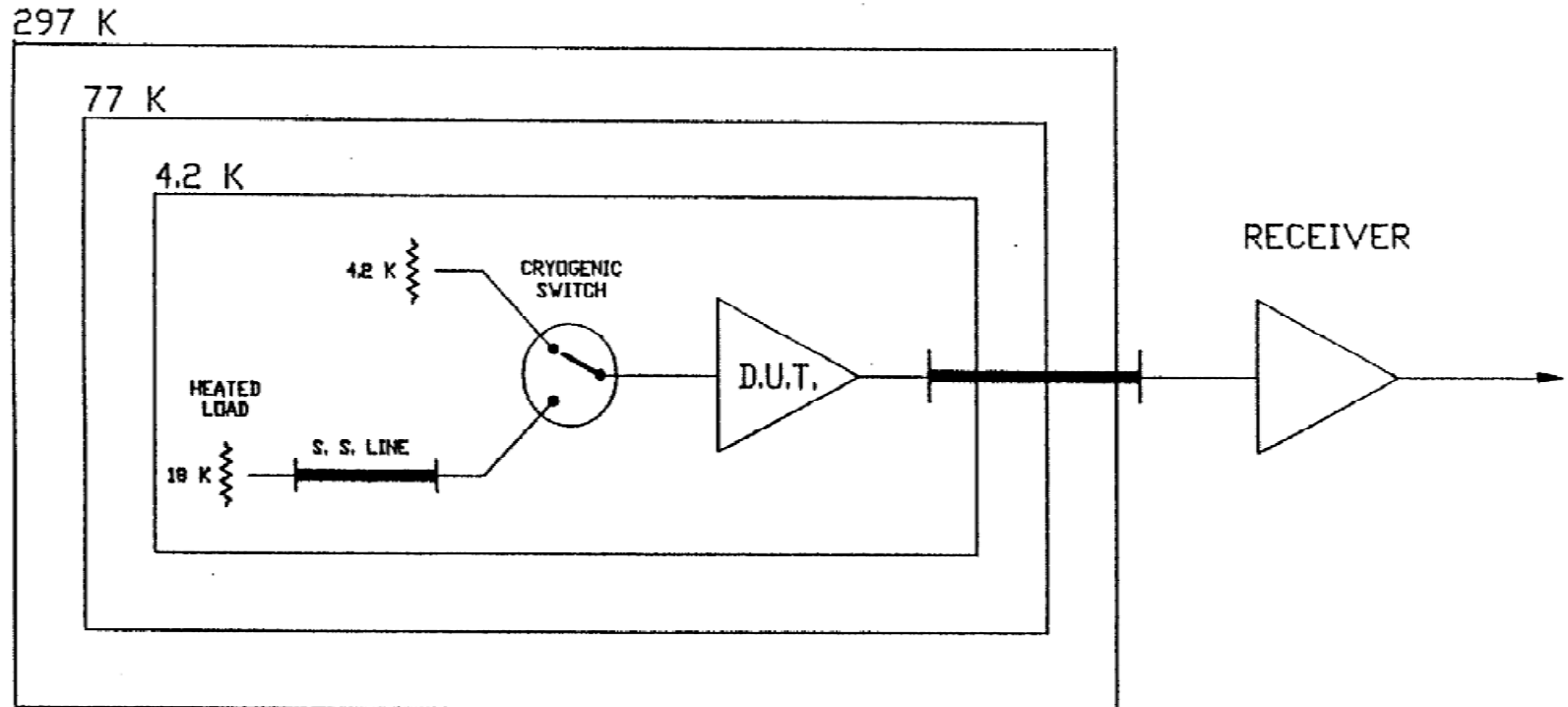


# Noise and Gain of 5-20 GHz Amplifier at $T_a=15$ K





# Hot-Cold Load Measurement Method



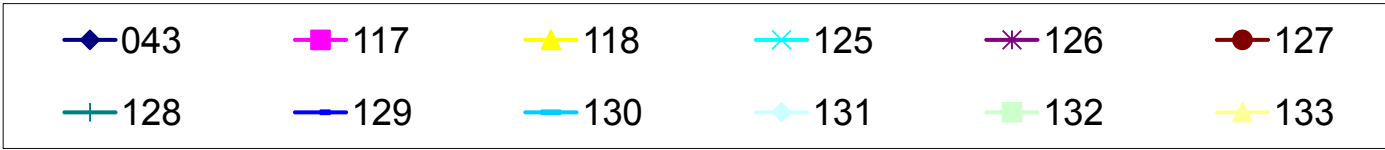
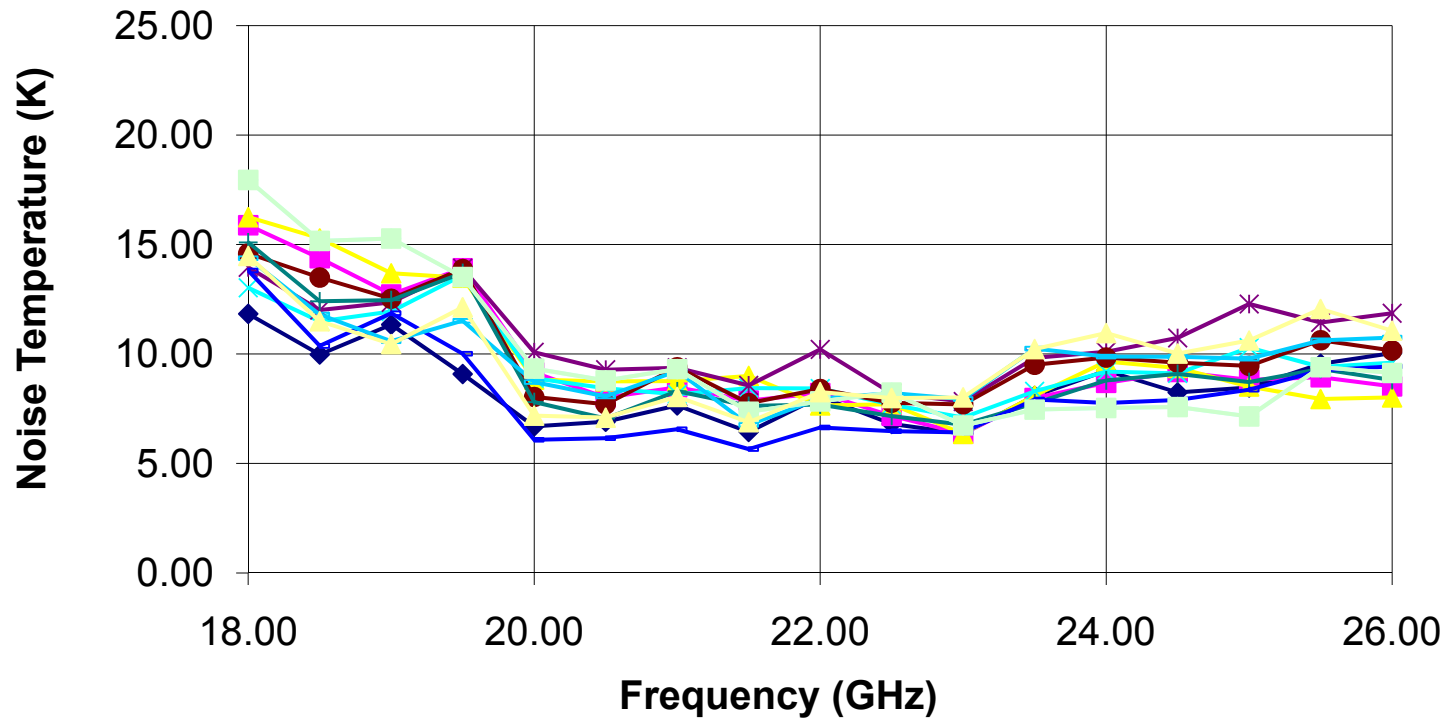
Sources of error:

- 1) Uncertainty in calibration of  $T_h$
- 2) Change in impedance of “hot” and “cold” state

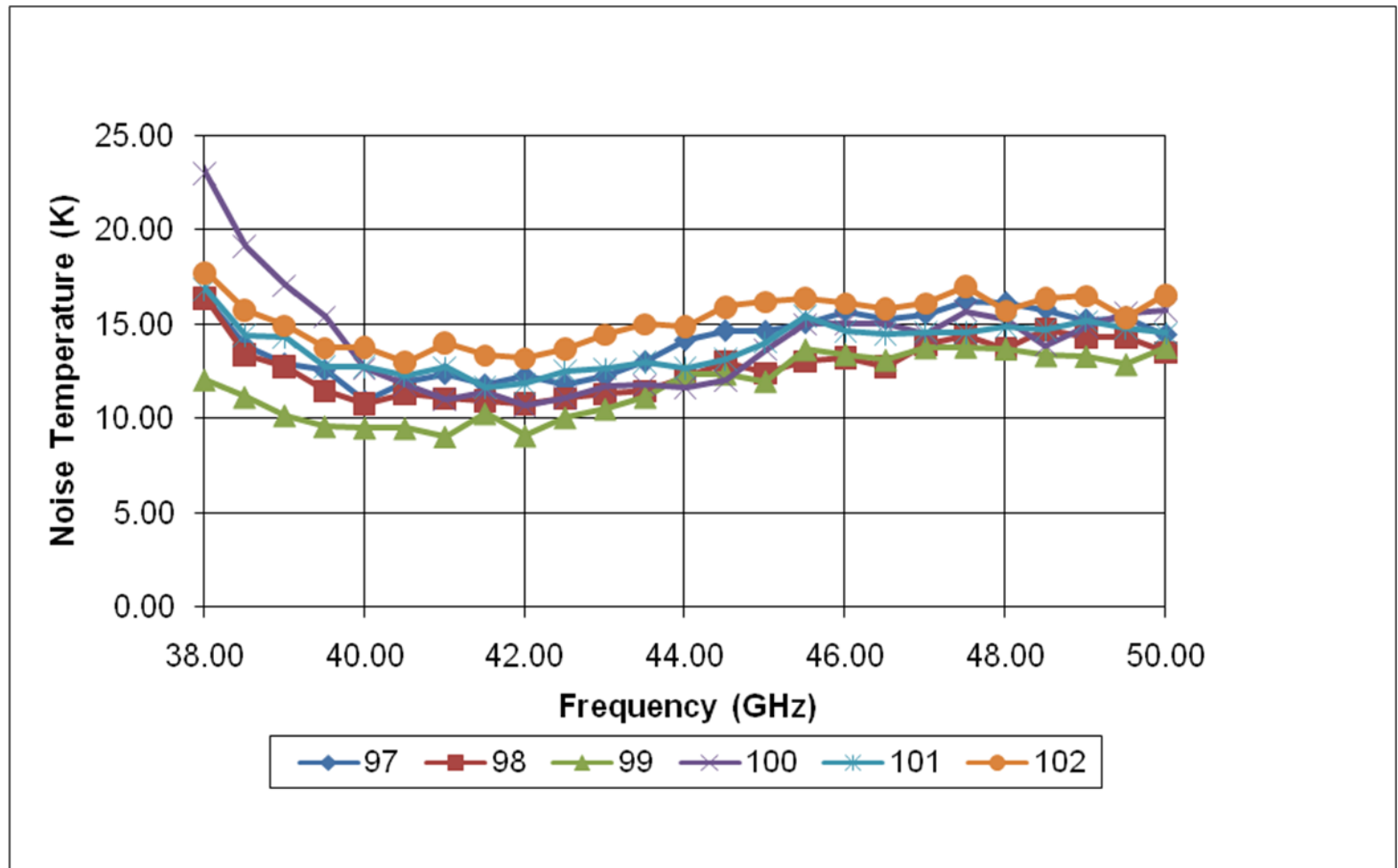
# Noise Measurements of Waveguide Amplifiers



# GBT K-Band Array Amplifiers at 19 K



# Noise Performance of Q-Band Amplifiers



# Sources of Error

- Uncertainty in calibration of  $T_h$  and  $T_c$
- Change in impedance of “hot” and “cold” state
- Receiver nonlinearity
- Receiver calibration
- Receiver stability
- Finite integration time for a given IF bandwidth

# Common Noise Representations of 2-Ports

$$T_n = T_{\min} + T_o \frac{g_n}{R_g} |Z_g - Z_{\text{opt}}|^2 = T_{\min} + NT_o \frac{|Z_g - Z_{\text{opt}}|^2}{R_g R_{\text{opt}}}$$

$$T_n = T_{\min} + 4NT_o \frac{|\Gamma_g - \Gamma_{\text{opt}}|^2}{\left(1 - |\Gamma_{\text{opt}}|^2\right) \left(1 - |\Gamma_g|^2\right)}$$

where  $\Gamma_{\text{opt}} = \frac{Z_{\text{opt}} - Z_o}{Z_{\text{opt}} + Z_o}$   $N = R_{\text{opt}} g_n$

For All Linear Noisy Two-Ports:  $T_{\min} \leq 4NT_o$



## Other Properties of Noise Parameters

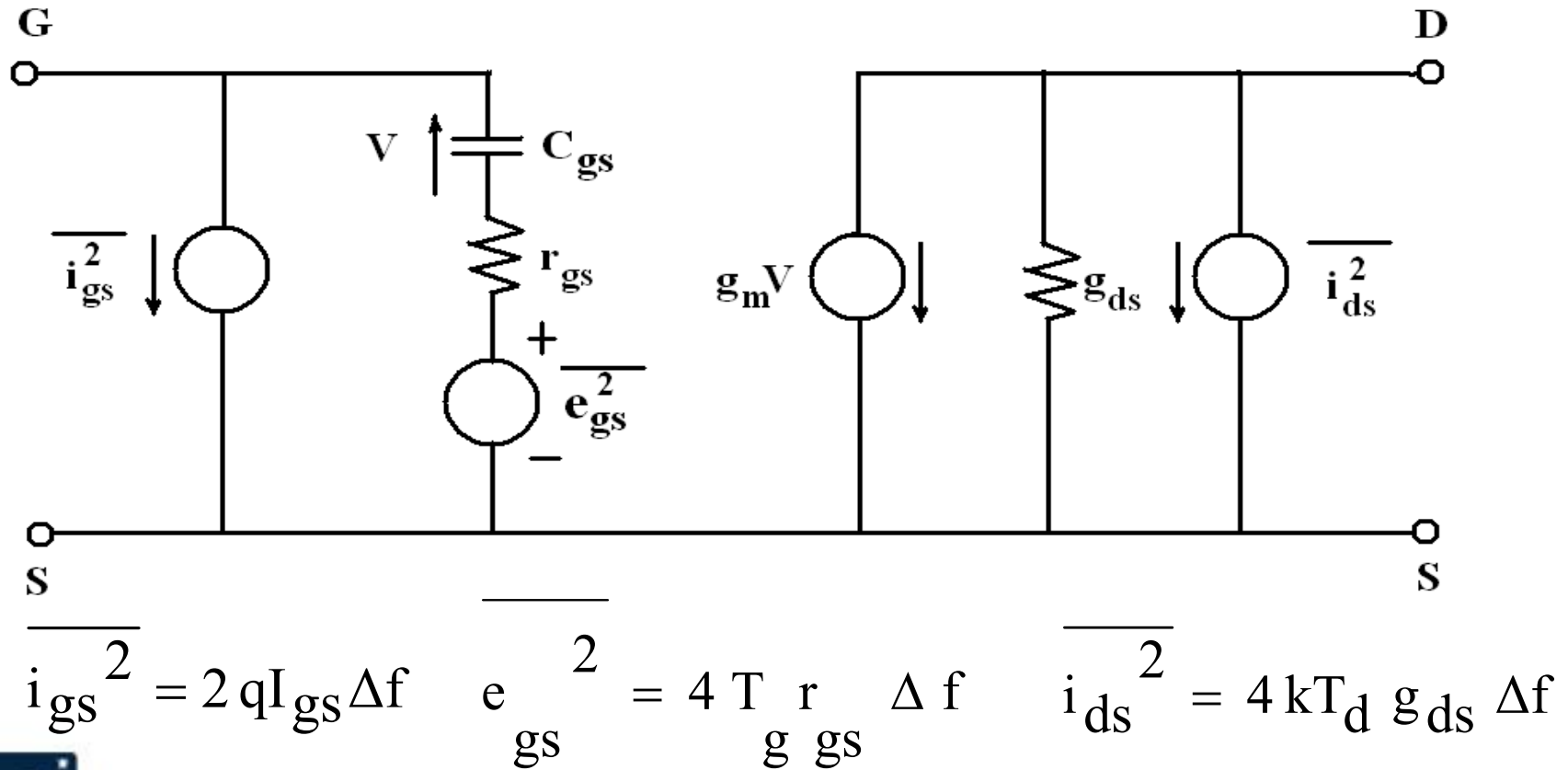
$$T_{\min} = T_0 \left\{ 2N + \operatorname{Re} \left( \rho \sqrt{R_n g_n} \right) \right\} .$$

Hence, 
$$1 \leq \frac{4NT_0}{T_{\min}} \leq 2$$

if and only if  $\operatorname{Re}(\rho) \geq 0$  and correlation matrix is Hermitian and non-negative definite.

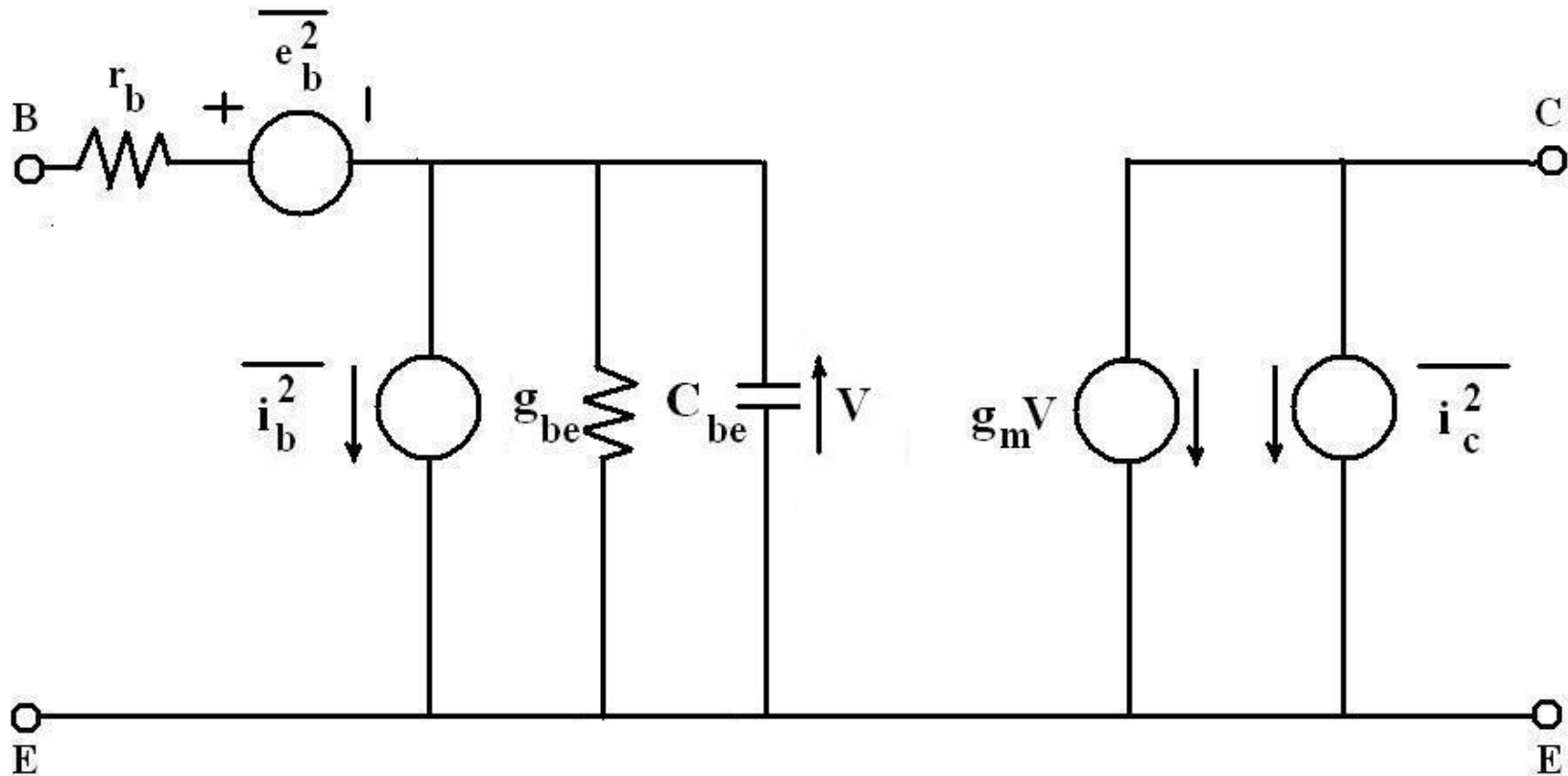
**It holds for generally accepted noise equivalent circuits of both FETs and HBTs.**

# Simplest Noise Equivalent Circuit of a FET





# Simplest Noise Equivalent Circuit of Intrinsic BT



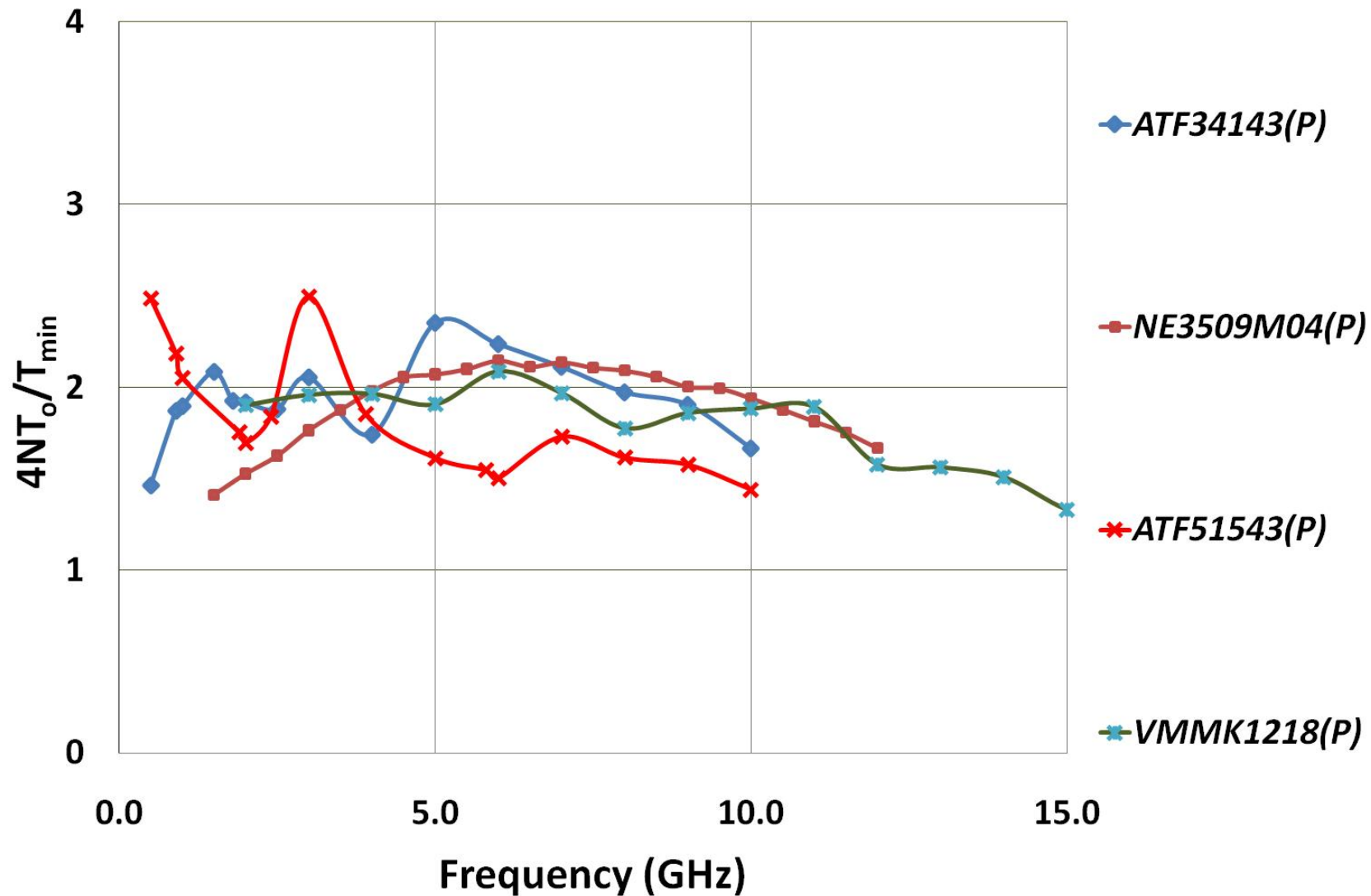
$$\overline{i_b^2} = 2 q I_{gs} \Delta f$$

$$\overline{e_b^2} = 4 k T_d r_b \Delta f$$

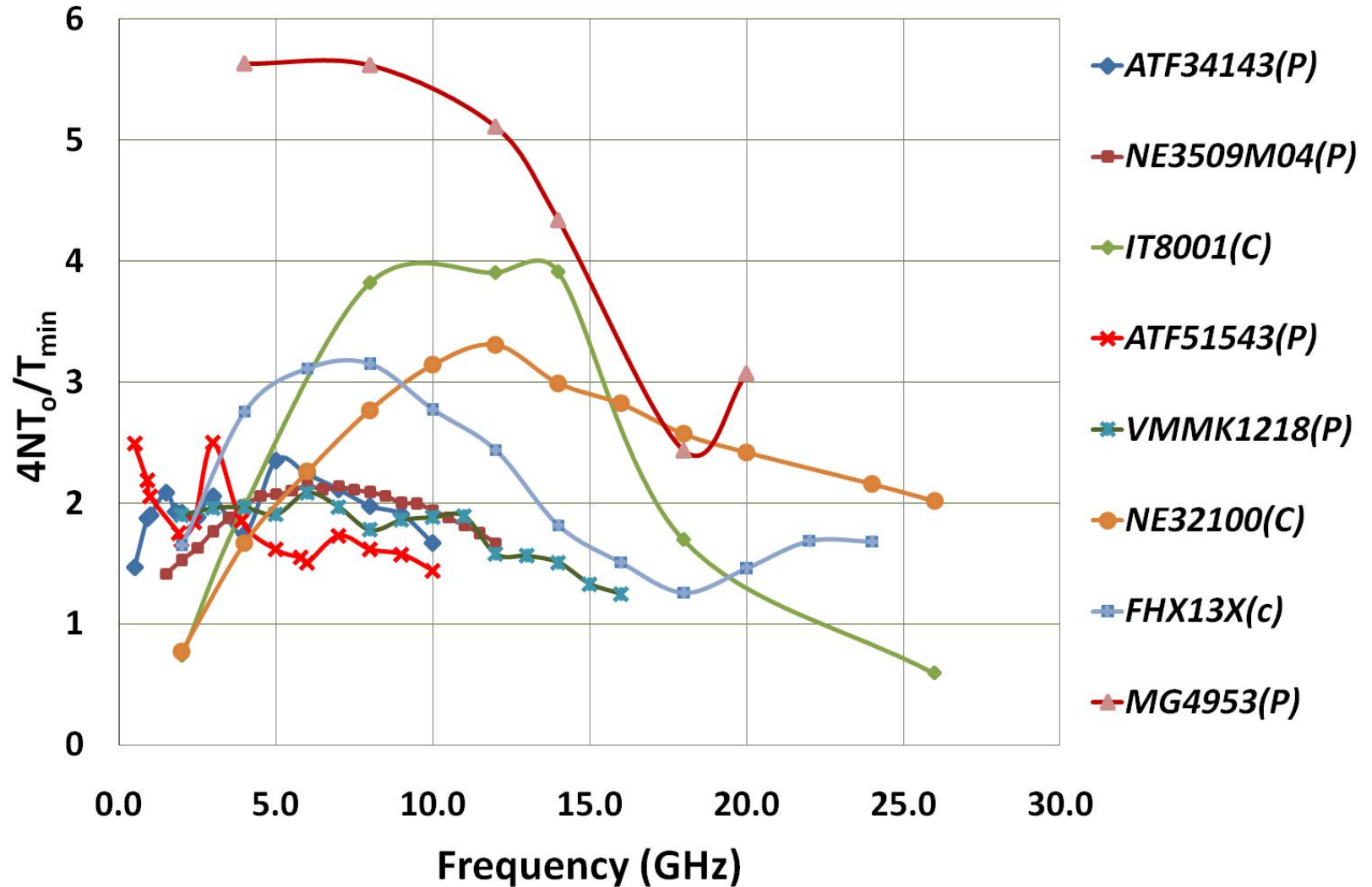
$$\overline{i_c^2} = 2 q I_c \Delta f$$



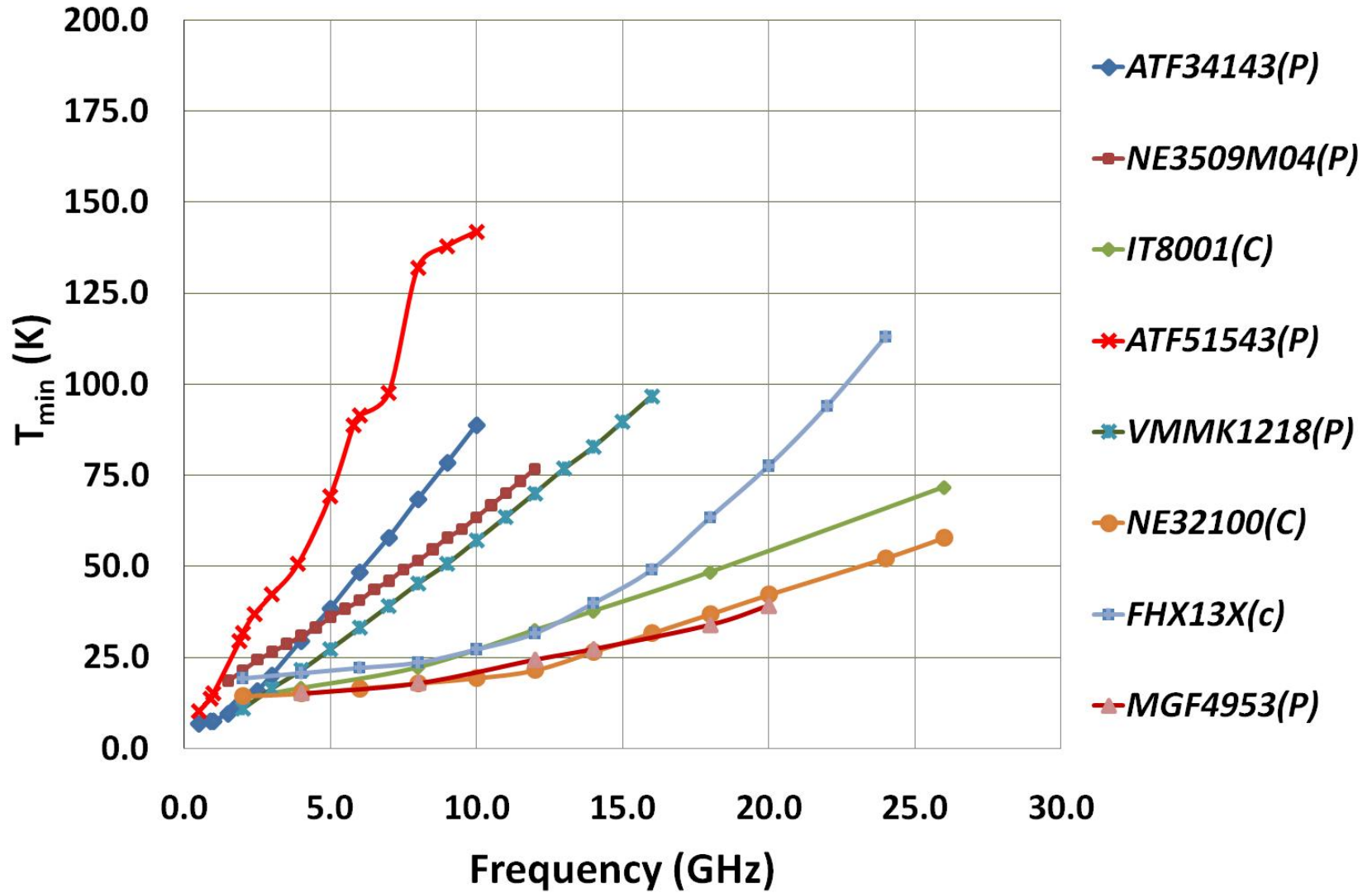
# $4NT_o/T_{\min}$ For Commercial Devices at 297 K (1)



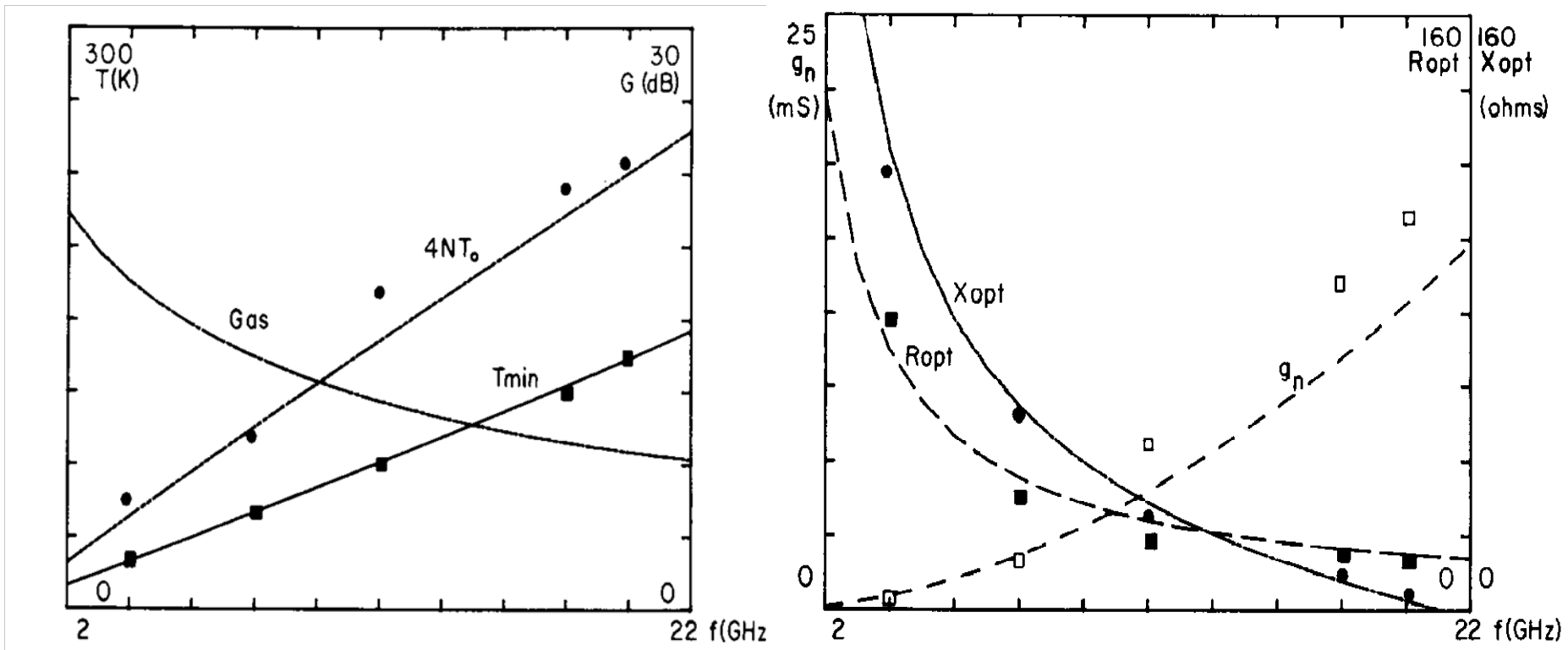
## 4NT<sub>o</sub>/T<sub>min</sub> For Commercial Devices at 297 K (2)



# $T_{\min}$ For Commercial Devices at 297 K

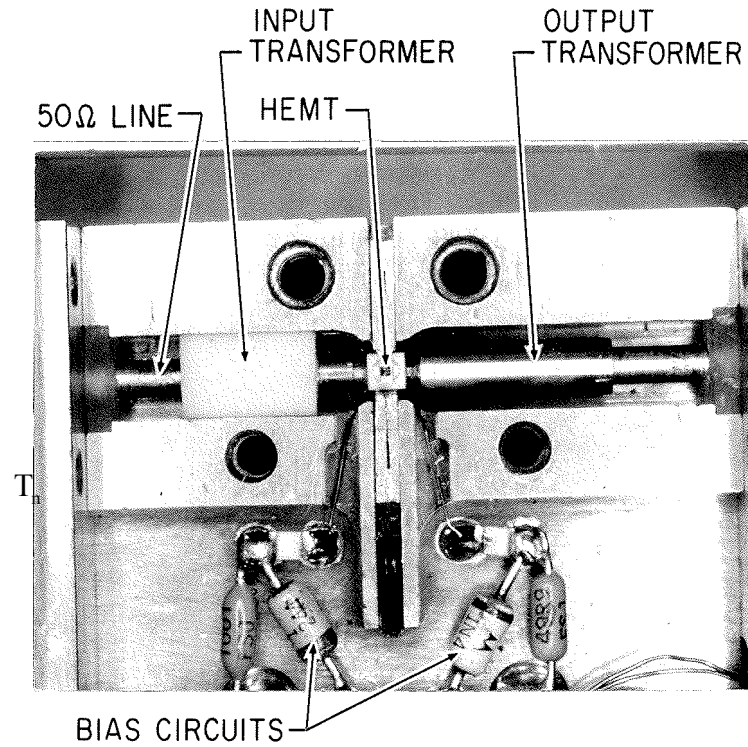
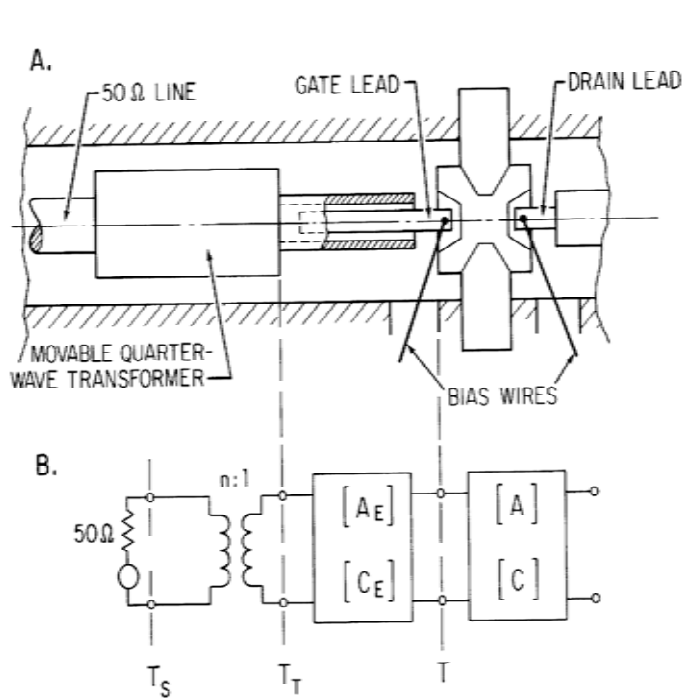


# Noise Parameters of FHR01X HEMT Chip(1989)



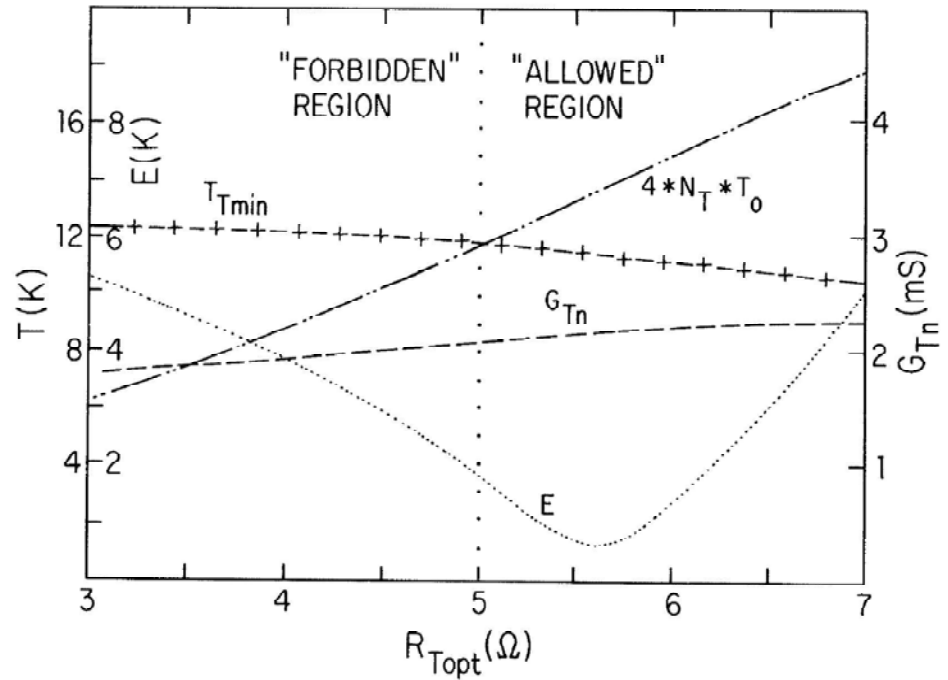
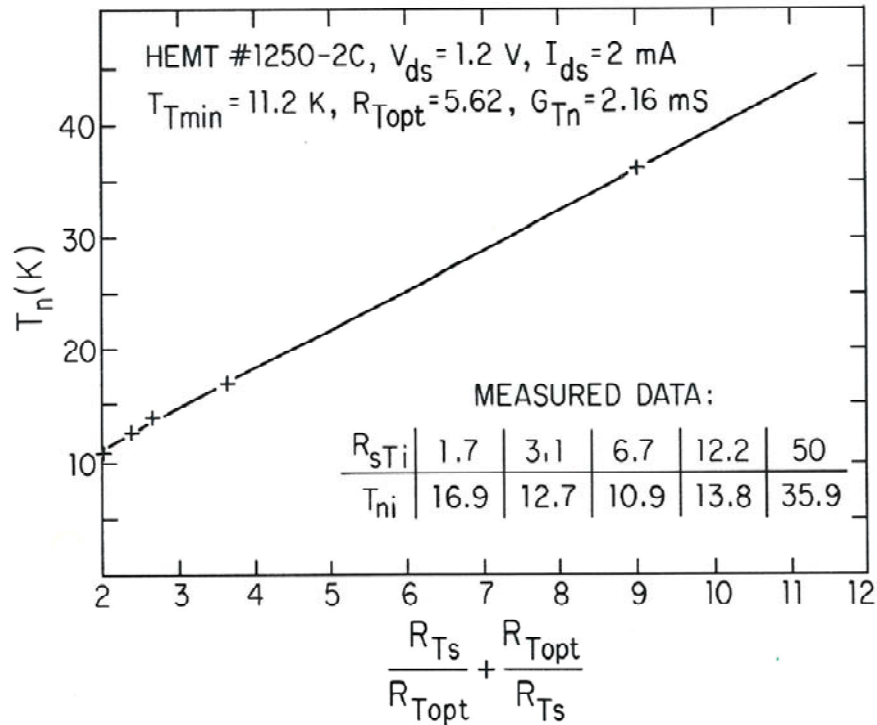
It was easier to measure devices accurately 20 years ago!!!

# A Method of Noise Parameters Measurement (1986)



$$\frac{T_n}{T_0} = \left( \frac{T_{\min}}{T_0} - 2N \right) + N \left( \frac{R_s}{R_{opt}} + \frac{R_{opt}}{R_s} \right)$$

# A Method of Noise Parameters Measurement (1986)



$$E = \sqrt{\sum_{i=1}^l (T_{ni}^m - T_{ni}^c)^2}$$

# Noise Parameters of FET: Approximation

For:  $\frac{f}{f_t} \ll \sqrt{\frac{T_g}{T_d} \frac{1}{r_{gs} g_{ds}}}$

$$R_{\text{opt}} \cong \frac{f_t}{f} \sqrt{\frac{r_{gs} T_g}{g_{ds} T_d}} \quad g_n = \left(\frac{f}{f_t}\right)^2 \frac{g_{ds} T_d}{T_o}$$

$$T_{\text{min}} \cong 2 \frac{f}{f_t} \sqrt{g_{ds} T_d r_{gs} T_g} \quad \frac{4NT_o}{T_{\text{min}}} \cong 2$$



# Broadband Matching Approximation

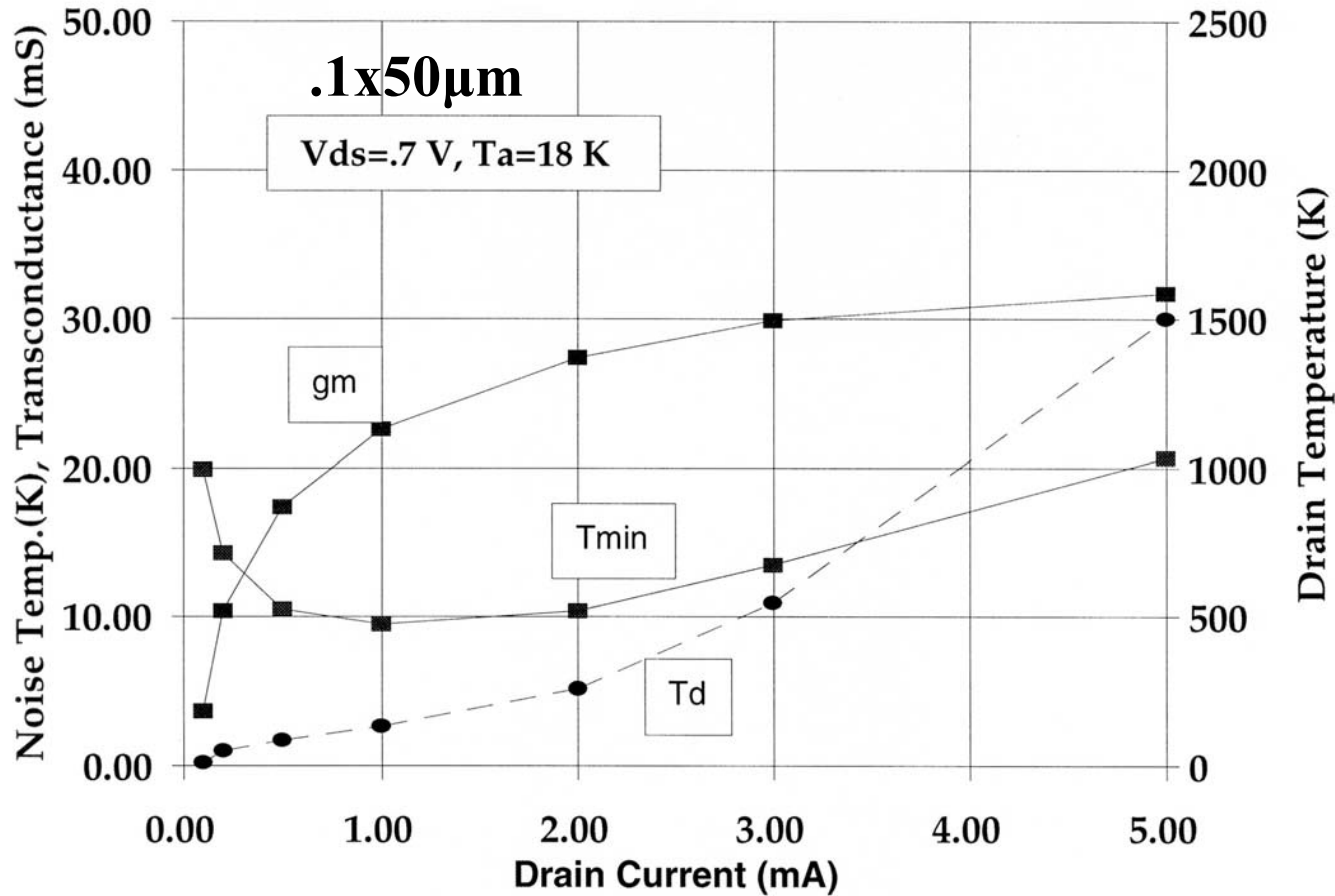
$$T_n = T_{\min} + 4NT_o \frac{|\Gamma_g - \Gamma_{\text{opt}}|^2}{\left(1 - |\Gamma_{\text{opt}}|^2\right)\left(1 - |\Gamma_g|^2\right)}$$

At some input plane of reference A :

$$T_{\min}^A = T_{\min} \quad N^A = N \quad \Gamma_g^A = 0$$

$$T_n^A = T_{\min} \frac{1 + |\Gamma_{\text{opt}}^A|^2}{1 - |\Gamma_{\text{opt}}^A|^2}$$

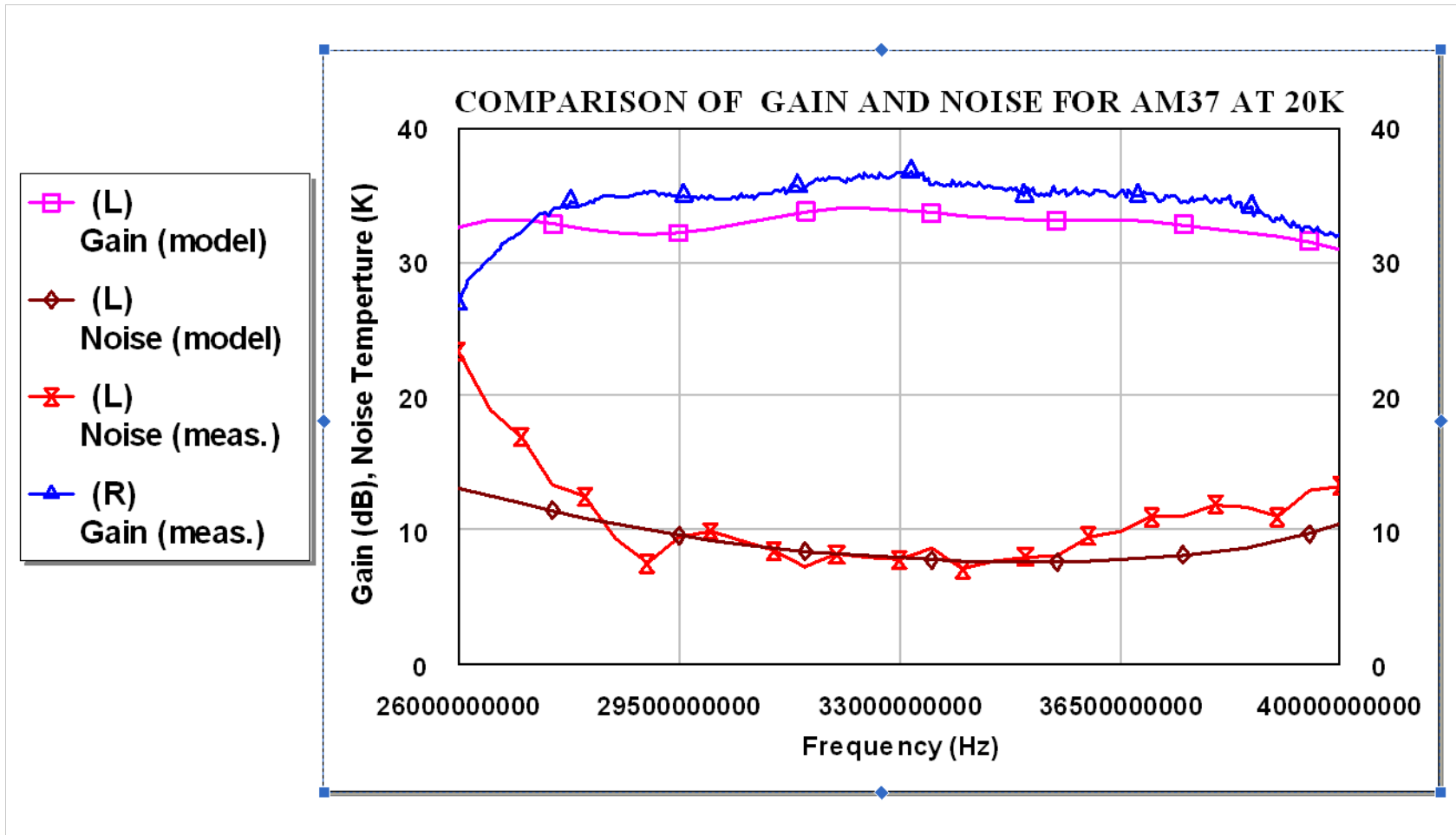
# Optimal Noise Bias of InP HFET at 18 K (1993)



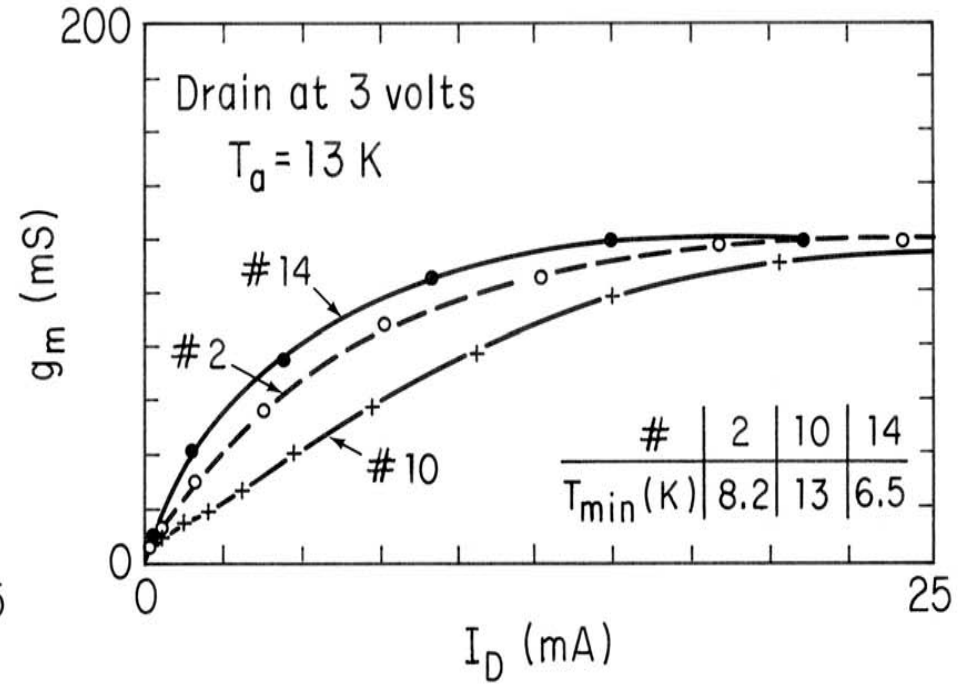
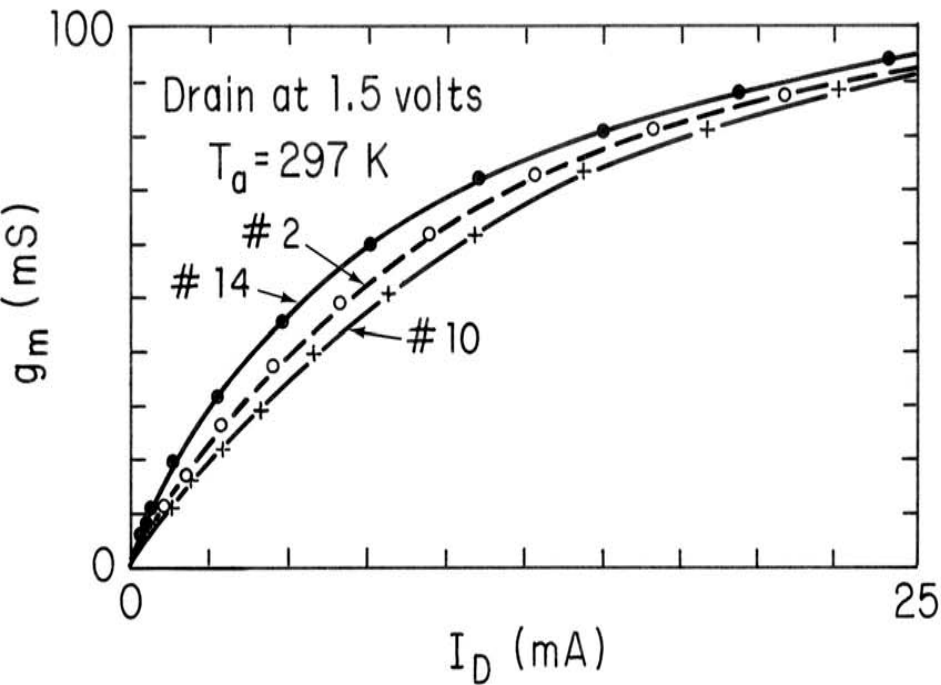
**Optimal bias minimizes the value of:**  $f(V_{ds}, I_{ds}) \approx \frac{\sqrt{T_d g_{ds}}}{f_t} \approx \frac{\sqrt{I_D}}{g_m}$



# EVLA K<sub>a</sub> Band Amplifier



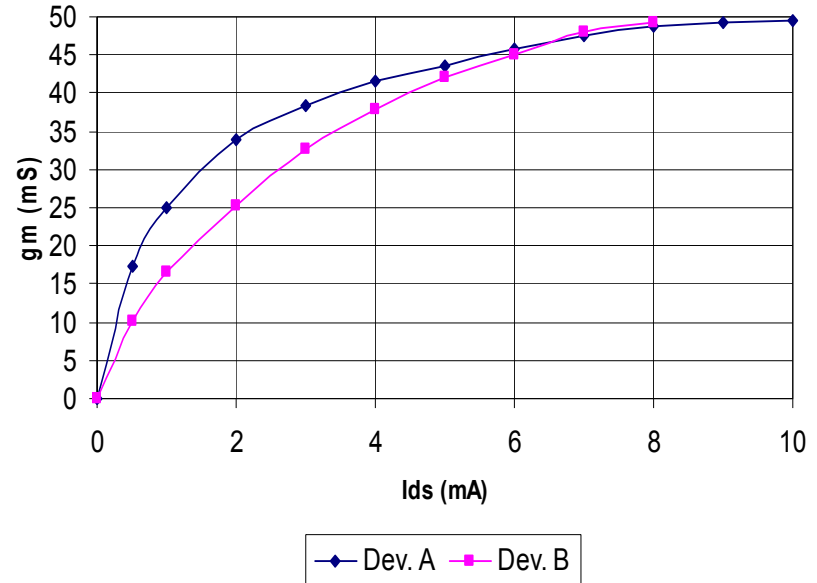
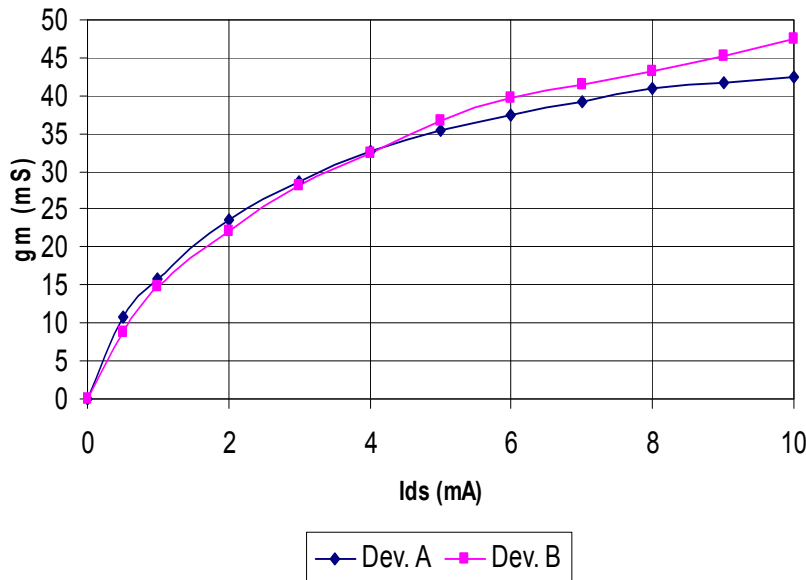
# Cryogenic $T_{\min}$ at 8.4 GHz and DC Pinch-off Characteristics of GE HFET's (1987)



# Example of “poor pinch off” InP HFET (1993)

$T_a=297\text{ K}$

$T_a=18\text{ K}$



$T_{\min}(297\text{ K})$

$T_{\min}(18\text{ K})$

at 40 GHz

Dev. A

148

12

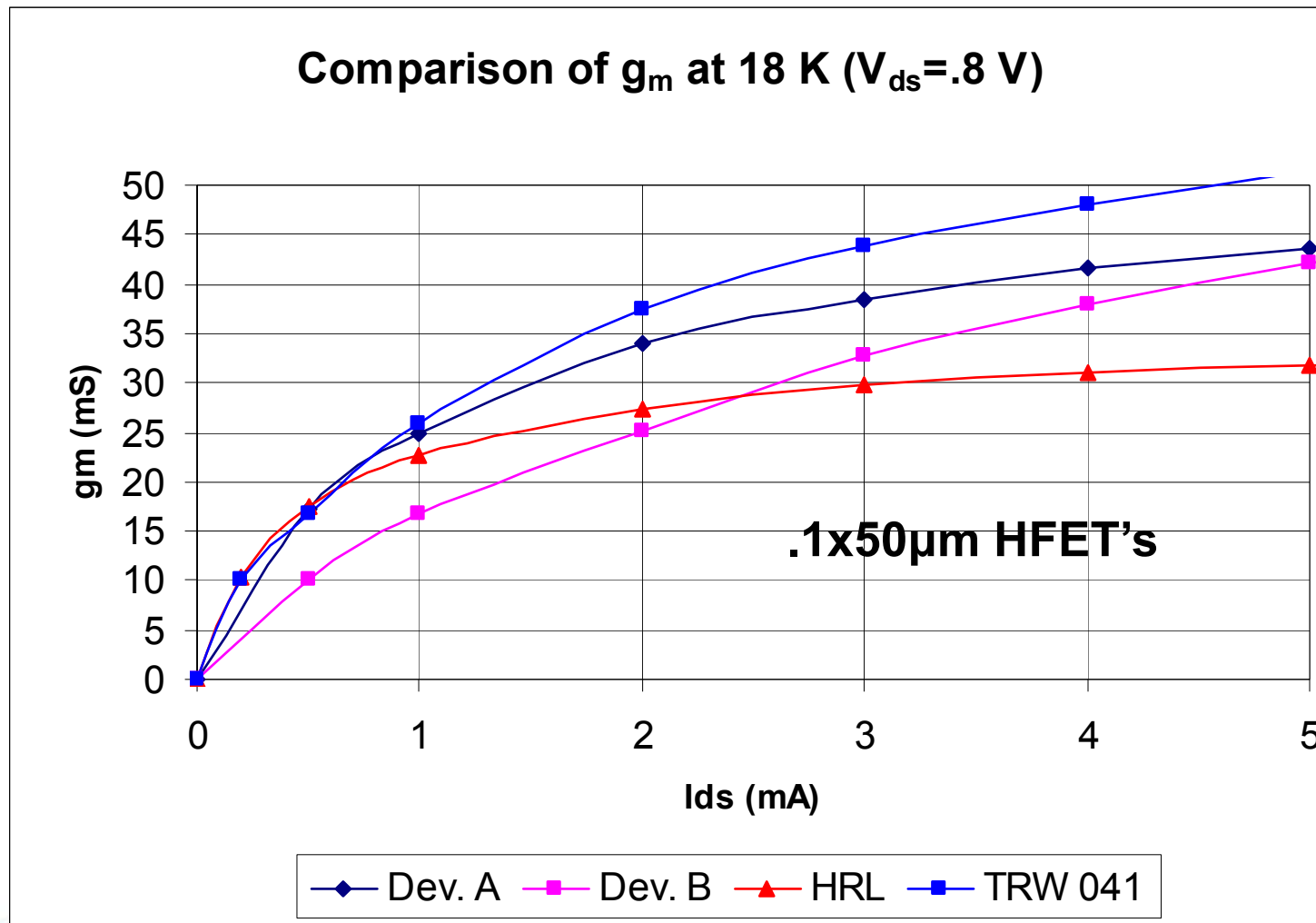
Dev. B

134

21



# Comparison of GE/MM, HRL and TRW HFET's



# Device Scaling: Gate Width

$$T_{\min} \cong 2 \frac{f}{f_t} \sqrt{g_{ds} T_d r_t T_g}$$

$$R_{\text{opt}} \cong \frac{f_t}{f} \sqrt{\frac{r_t T_g}{g_{ds} T_d}}$$

$$r_t = r_{gs} + r_g + r_s$$

$$f(V_{ds}, I_{ds}) \approx \frac{\sqrt{T_d g_{ds}}}{f_t} \approx \frac{\sqrt{I_D}}{g_m}$$

Width 

$R_{\text{opt}}$  

$T_{\min}$  

in principle

$T_{\min}$  

in practice

# Device Scaling: Gate Length

$$T_{\min} \cong 2 \frac{f}{f_t} \sqrt{g_{ds} T_d r_t T_g} \qquad f_t \cong \frac{g_m}{2\pi(C_{gs} + C_{gd})}$$



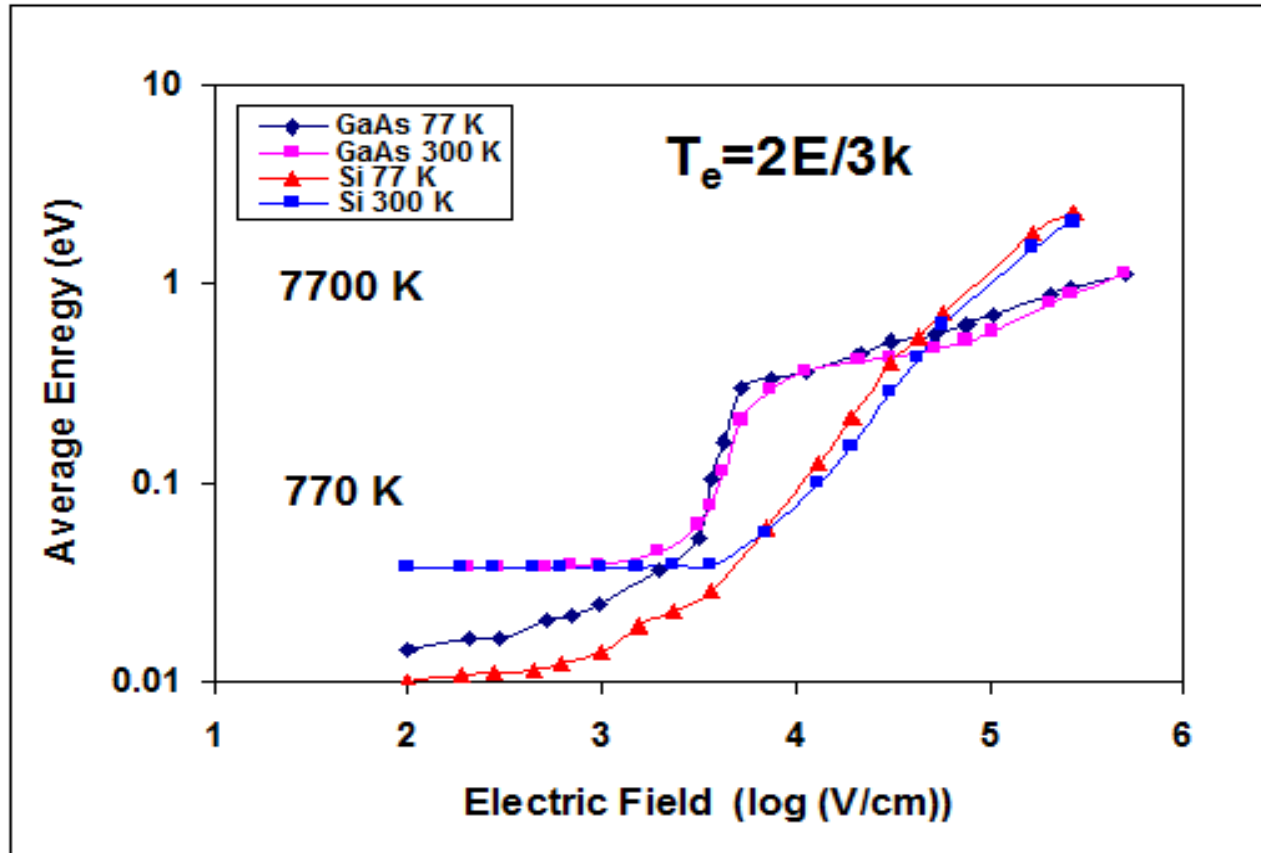
$T_g \cong$  Ambient temp.      $T_d$  depends on channel structure and current  $I_d$  but mostly not on ambient temperature

For every wafer structure there must exist a lower limit on  $T_{\min}$  upon further device scaling

Dependence of  $T_d$  on device structure and properties of electron transport in the channel is not known



# “Hot electron” noise



After Fischetti, IEEE Trans. ED vol. 38, p.634, March 1991

## To Cool or Not to Cool

1). No cryogenic performance can be predicted from room temperature performance

2). For well behaved cryo-devices the rule of thumb for amplifiers are:

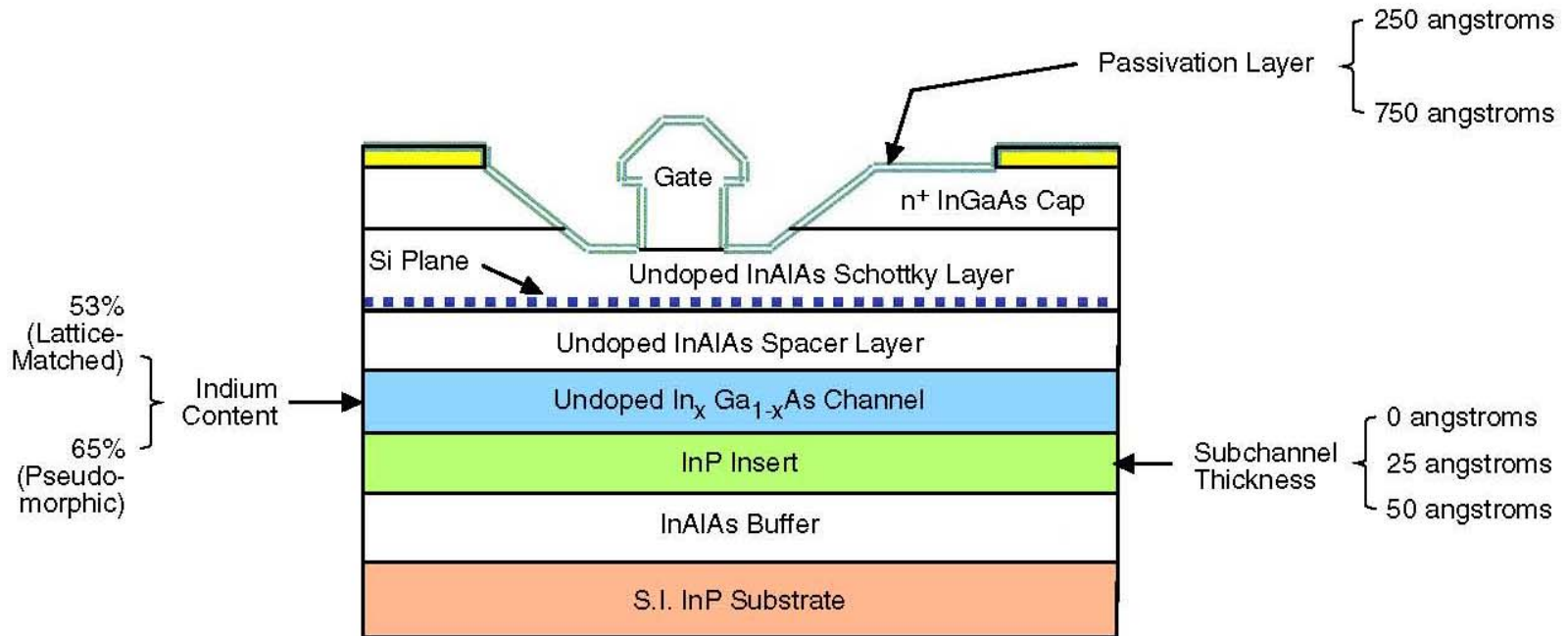
$$T_n(77\text{K}) \approx \sqrt{5} \times T_n(15\text{K})$$

No change in bias upon cooling

$$T_n(297\text{K}) \approx 10 \times T_n(15\text{K})$$

Optimal bias at each temperature

# NGST/JPL CRYO3 WAFER



Wafer 4099-040 (Pseudomorphic InGaAs Channel, 750 Å Passivation Layer, 50 Å InP Insert)

Wafer 4044-041 (Pseudomorphic InGaAs Channel, 250 Å Passivation Layer, 25 Å InP Insert)

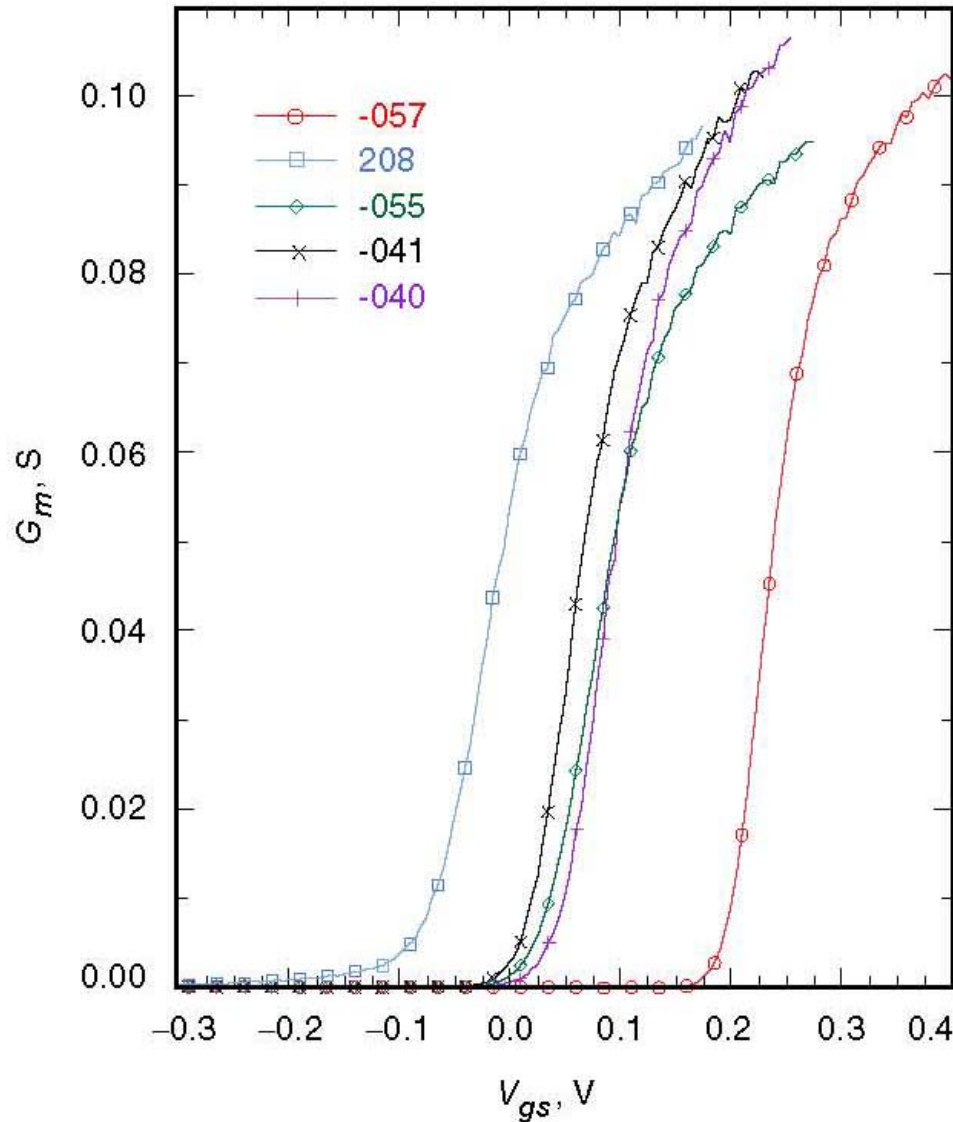
Wafer 4080-055 (Lattice-Matched InGaAs Channel, 750 Å Passivation Layer, 25 Å InP Insert)

Wafer 4080-057 (Lattice-Matched InGaAs Channel, 750 Å Passivation Layer, 50 Å InP Insert)

Wafer 4074-090 (Pseudomorphic InGaAs Channel, 750 Å Passivation Layer, No InP Insert)

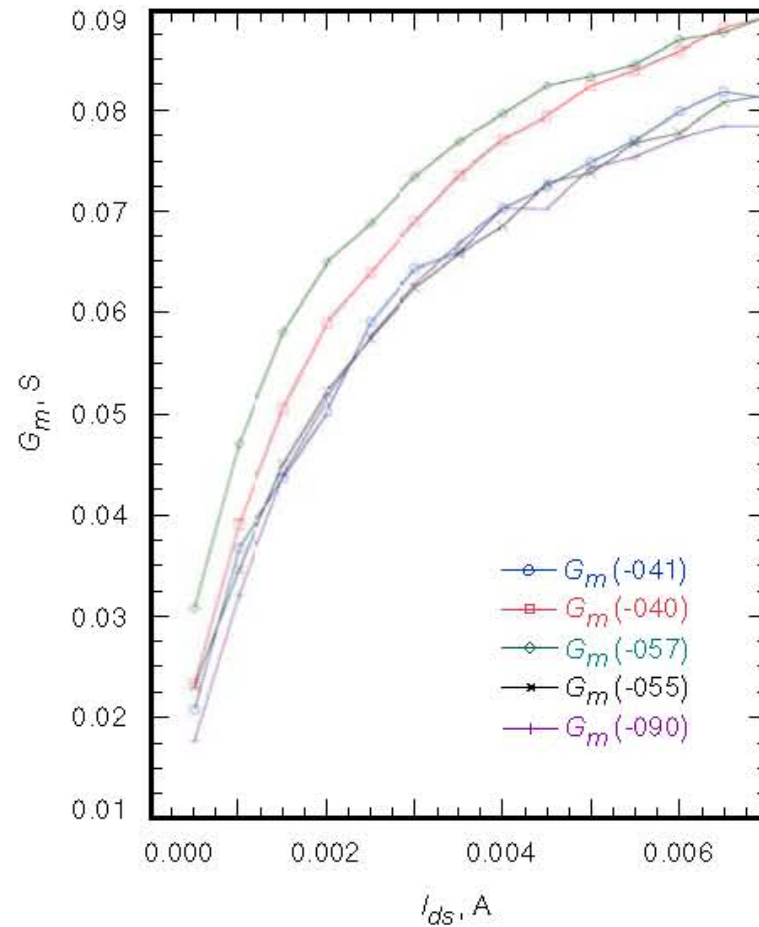
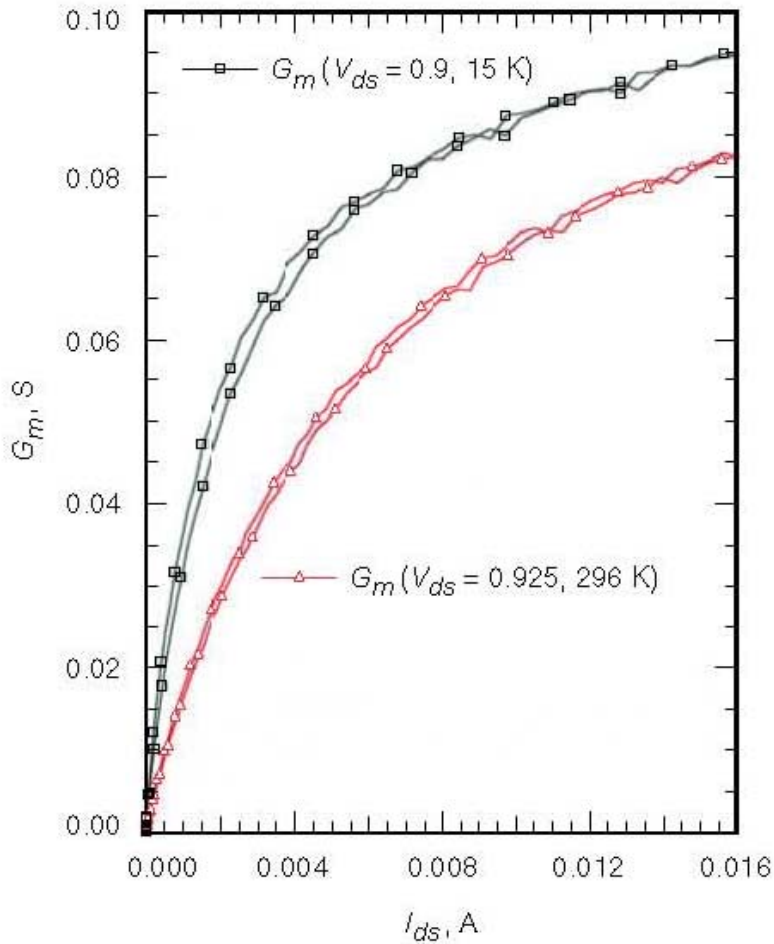
Wafer 4094-038 (Pseudomorphic InGaAs Channel, 250 Å Passivation Layer, No InP Insert)  
(This Wafer Did Not Survive Processing)

# Cryo3 Wafer $g_m$ vs $V_{gs}$



J.Shell, IPN Progress  
Report 42-169, JPL,  
May 2007

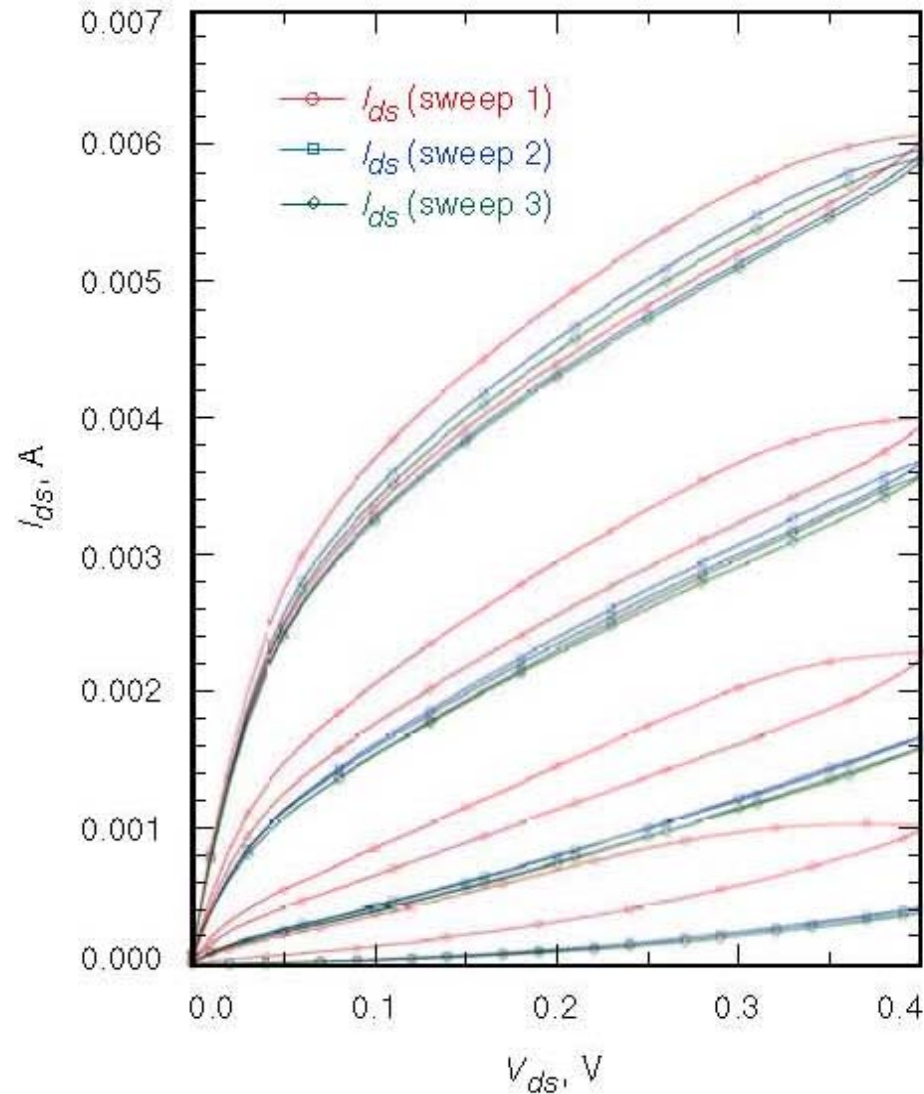
# Cryo3 Wafer $g_m$ vs $V_{gs}$



J.Shell, IPN Progress Report 42-169, JPL, May 2007



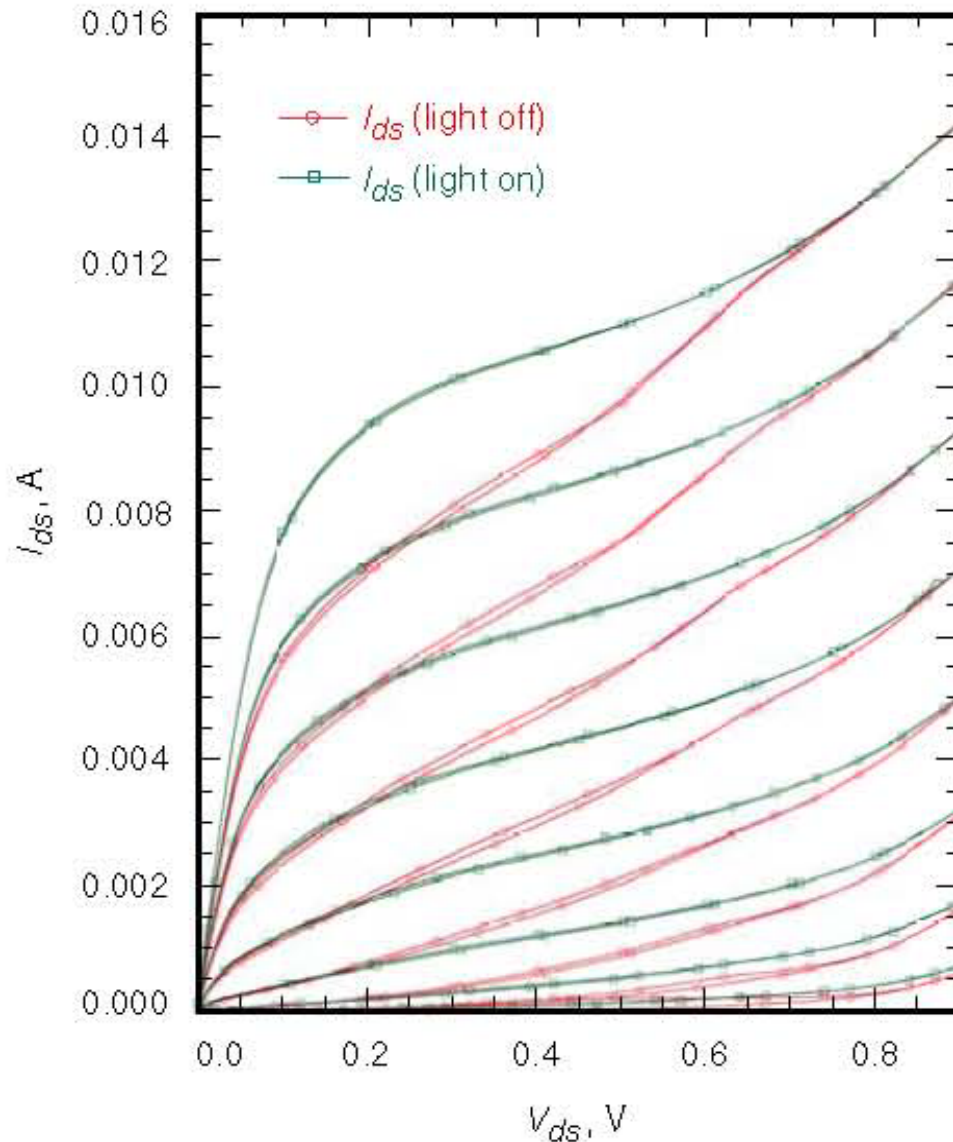
# Cryo3 Wafer $g_m$ vs $V_{gs}$



Double sweeps  
taken in fast  
succession

J.Shell, IPN Progress  
Report 42-169, JPL,  
May 2007

# Cryo3 041 Wafer I-V Characteristics



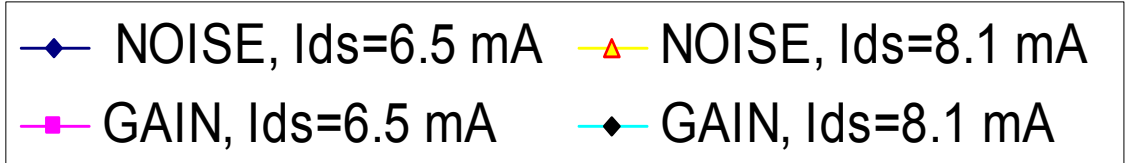
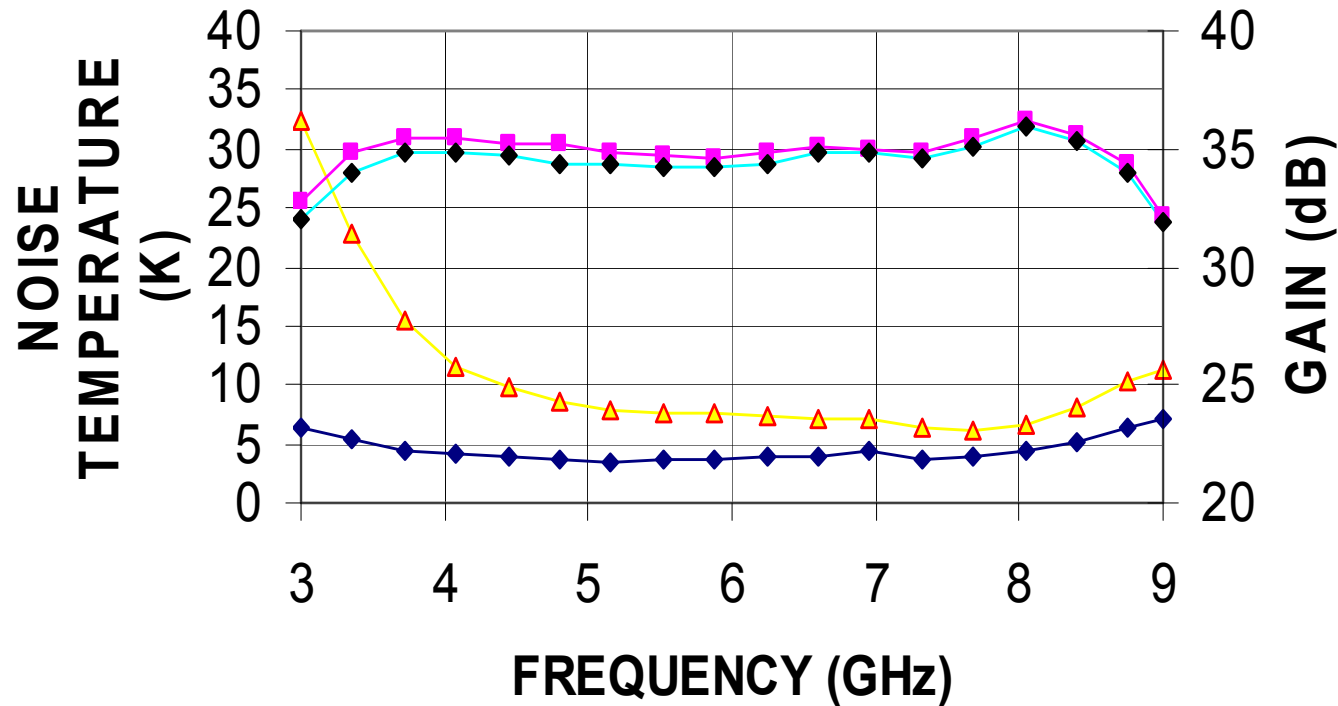
J.Shell, IPN Progress  
Report 42-169, JPL,  
May 2007

# Cryo3 Questions Still Open:

- 300  $\mu\text{m}$  wide InP HFET's do not behave as expected from scaling (this applies to all the discrete wafers evaluated at NRAO)
- 200  $\mu\text{m}$  from cryo3 wafer exhibit a very strong dependence of noise on drain voltage at L, S and C bands
- 80 and 60 $\mu\text{m}$  wide devices from cryo3 4044-041 wafer exhibit (sometimes) dc instability which seems to be related to device layout



# 4\_8 GHz AMPLIFIER AT 15 K



# Final Observations

- Only three wafer runs of InP discrete devices (NRAO/HRL, WMAP/HRL, NGST/JPL cryo3) have been used in construction of great majority of amplifiers for radio astronomy (VLA/EVLA, VLBA, GBT, ALMA band6, CBI, SZ-Array, WMAP, Planck LFI, VSA, AMI, MPI, JPL/DSN and others)
- No single wafer devices have ever been fully understood
- There has been no significant progress in the low noise performance of cryogenic FET's for the past 16 years; Are we approaching the limits?
- Amplifier noise temperature is no longer the dominant component of the system noise for radio astronomy instruments with cryogenic receivers